



SENSiC^{·CH}



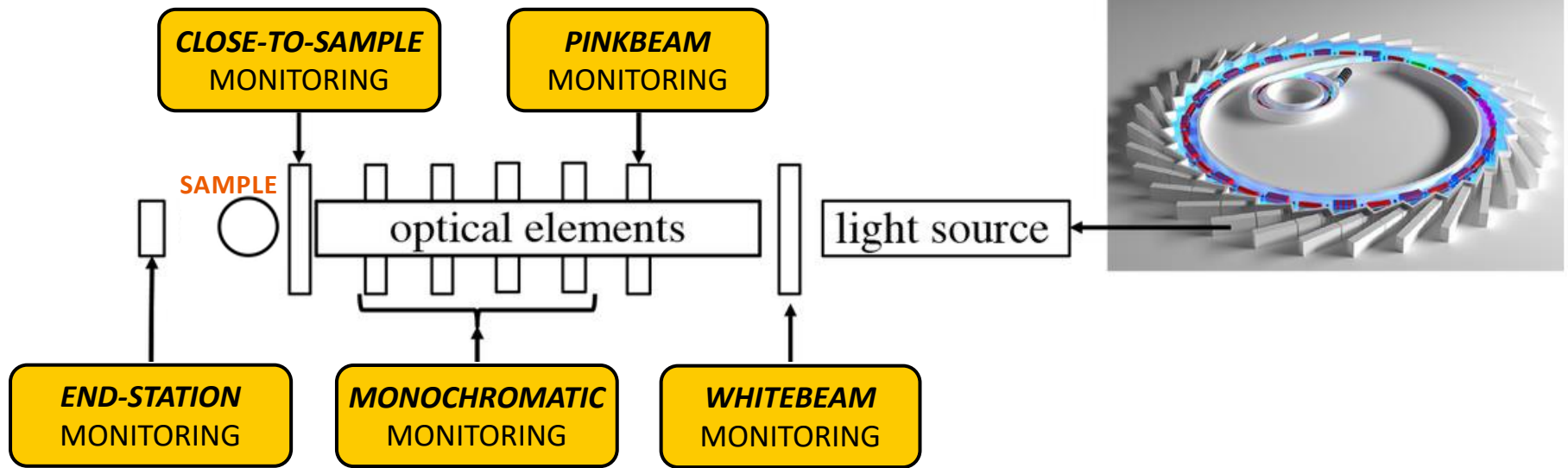
Silicon Carbide X-ray diagnostic

Massimo Camarda, SenSiC GbmH, Switzerland

massimo.camarda@SenSiC.ch

- Introduction to synchrotron beam monitoring
 - Current applications of SiC XBPMs at microXAS@SLS
- Whitebeam and cross-chromatic monitoring
 - Comparisons between hard and soft beamlines @ SLS
 - Example of 6GeV Engineering materials beamline @ HEPS
- Conclusions and outlooks
- Q&E

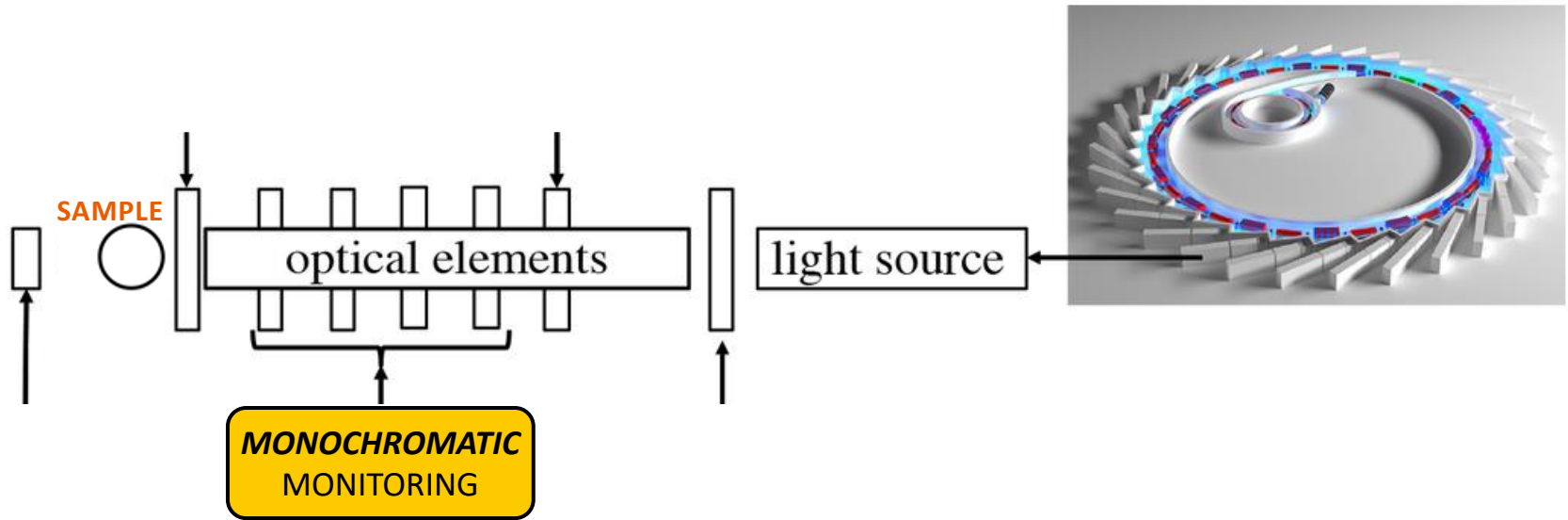
Generalities of Synchrotron Beam monitoring



Main requirements

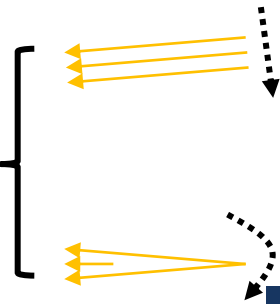
- transparency (>98%)
- stability over time
- good lateral resolution (<um)
- fast response (<ms, <us)
- large active areas (mm²)

Generalities of Synchrotron Beam monitoring

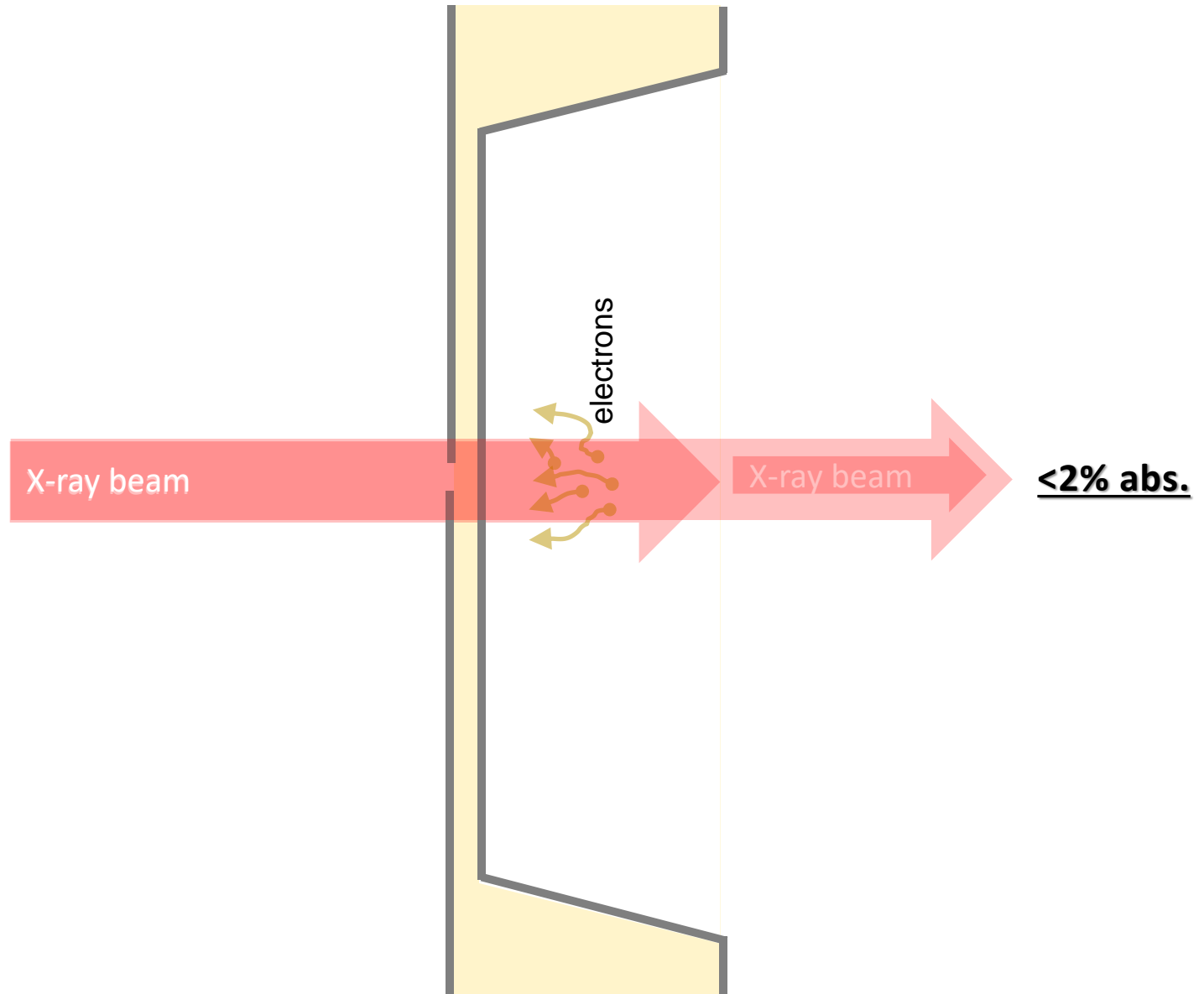


Commercially available XBPM

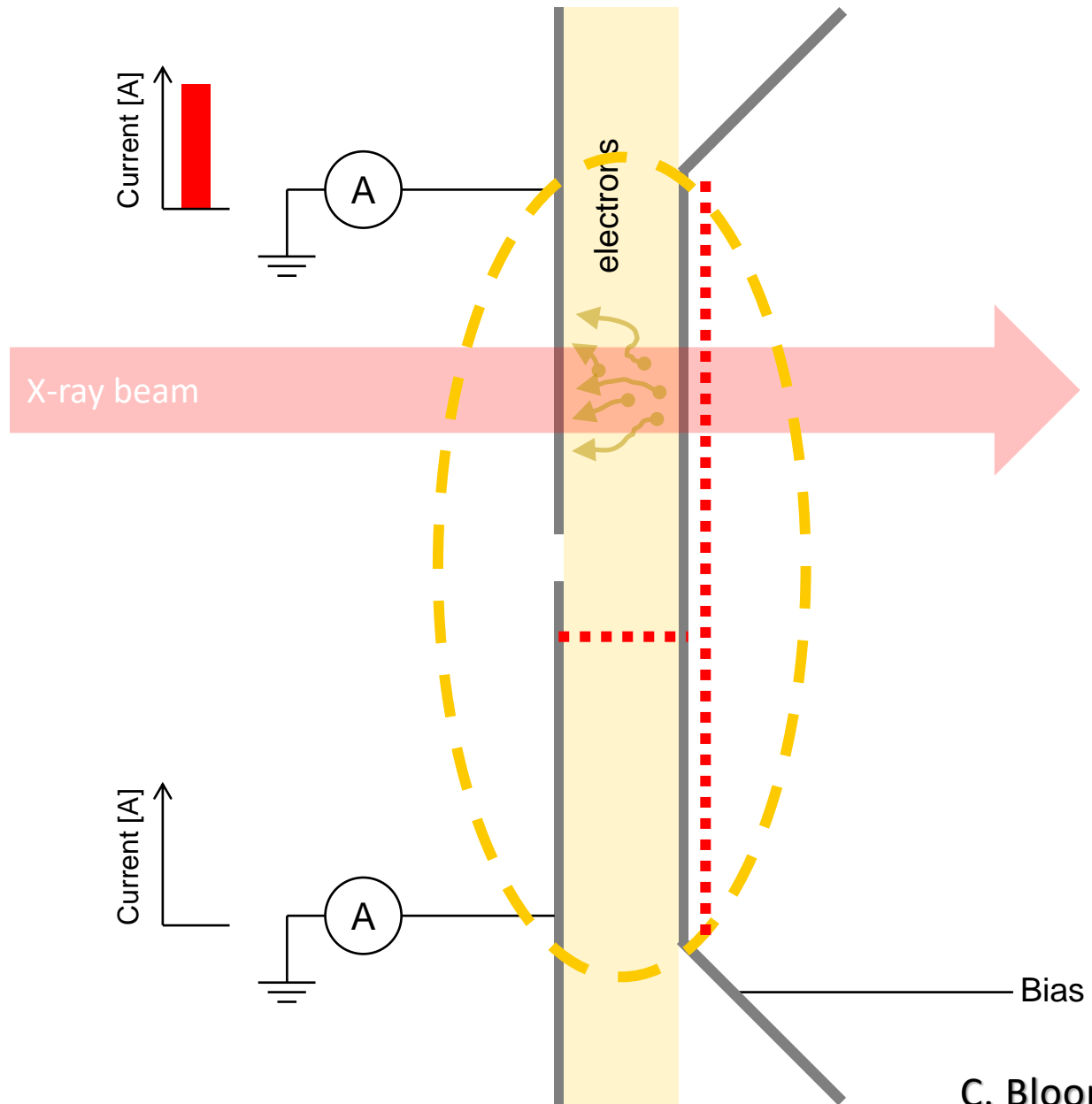
- 1) Monochromatic
- 2) *Hard-Xray*
- 3) *Position*
- 4) Only on *single-feedback* schema



Standard "thin-membrane" solid state XBPM



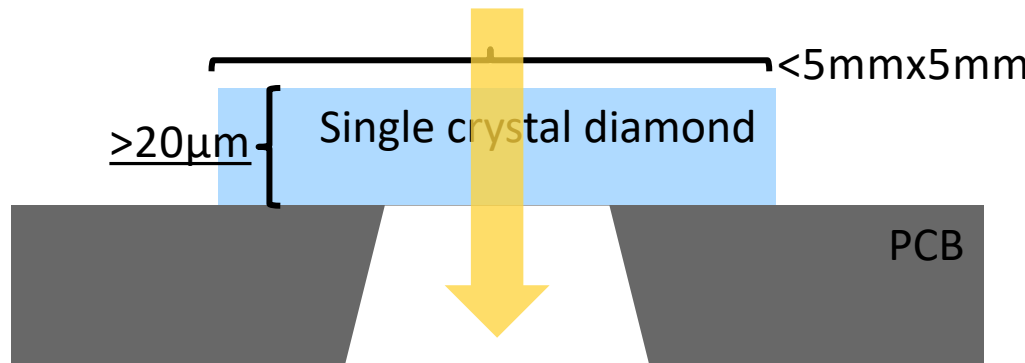
Standard "thin-membrane" XBPM



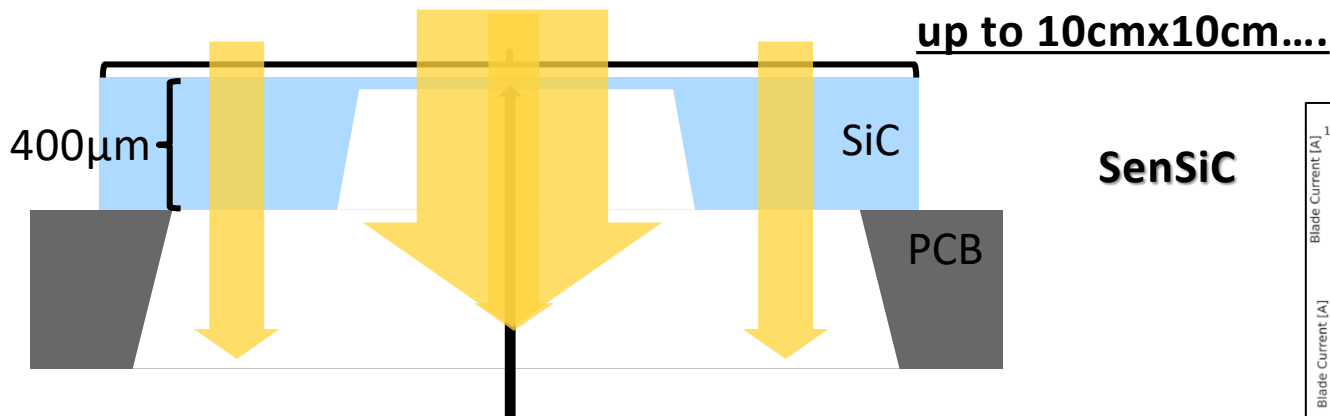
Comparison between Diamond and Silicon Carbide XBPM

“A comparison between single crystal diamond and SiC X-ray beam position monitors”

HOUGHTON, Diamond Light Source, SRI/JSR



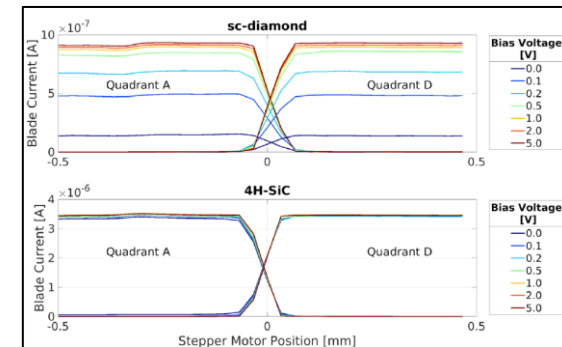
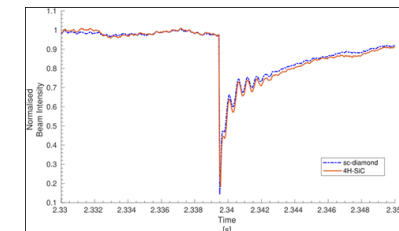
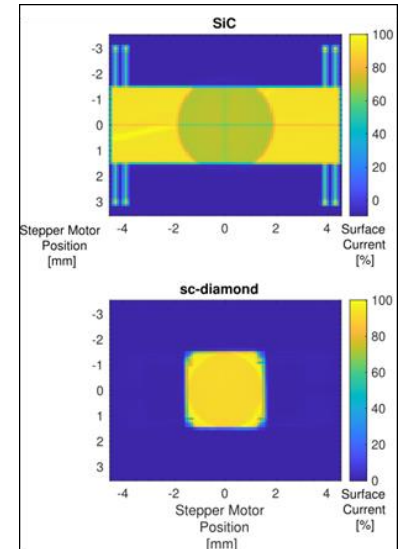
**CIVIDEC
SYDOR**



SenSiC

ultra-thin (framed) membrane!

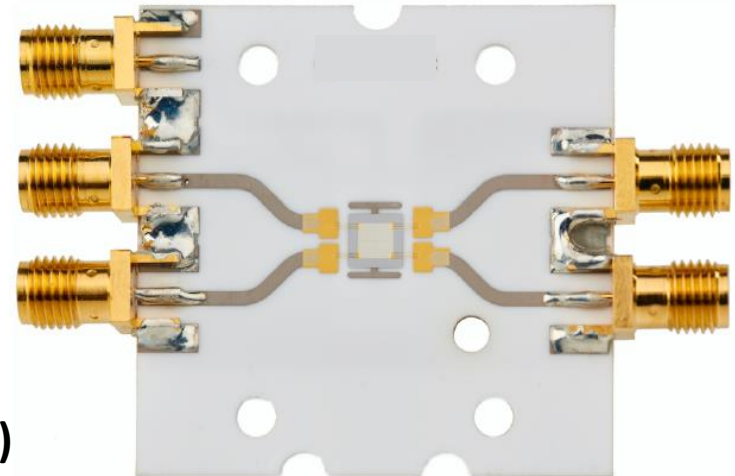
massimo.camarda@SenSiC.ch



*up to instrumental limits

Why choose Silicon Carbide XBPMs?

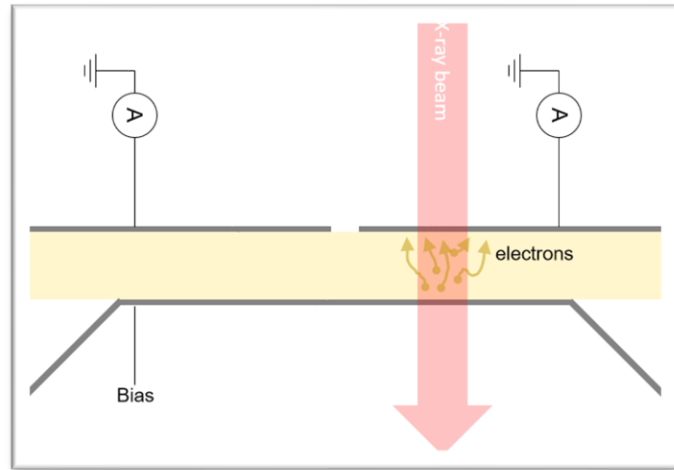
- Lower device costs
- Larger active areas (up to x9 time higher)
- Higher current signals / higher resolutions*
- Superior transparencies (20 μ m, 2 μ m, 1 μ m, 0.2 μ m)
- easier installations:
 - zero bias operation
 - test of devices without beam
- Short delivery times
- Large number of devices quickly available



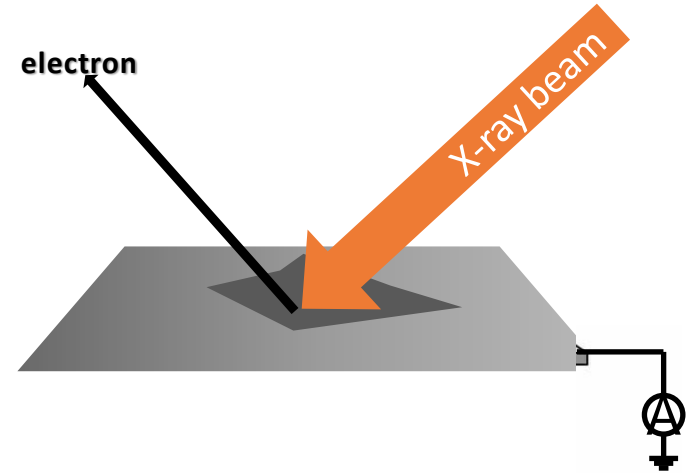
*for equivalent sensor geometries

Comparison of X-ray sensors

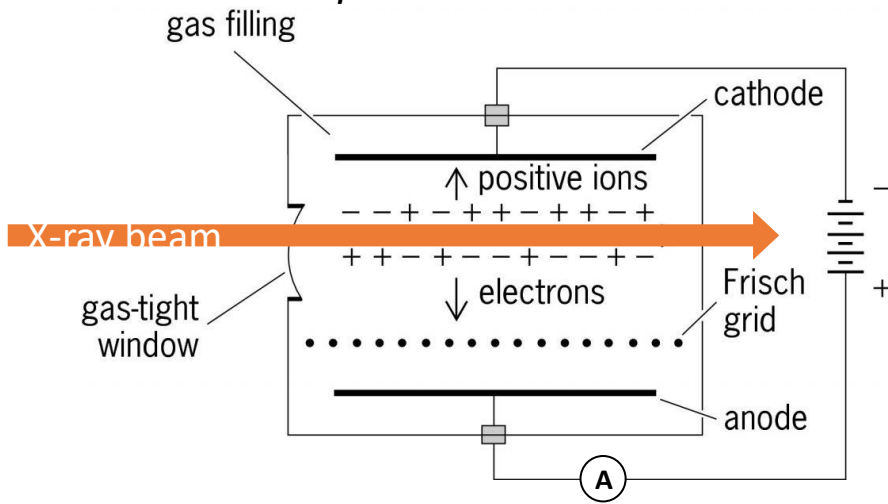
semiconductor based
internal photoemission



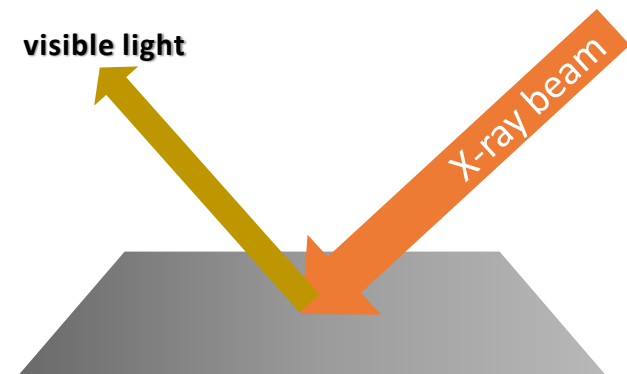
metal based
external photoemission



gas based
photoionization



fluorescence screen

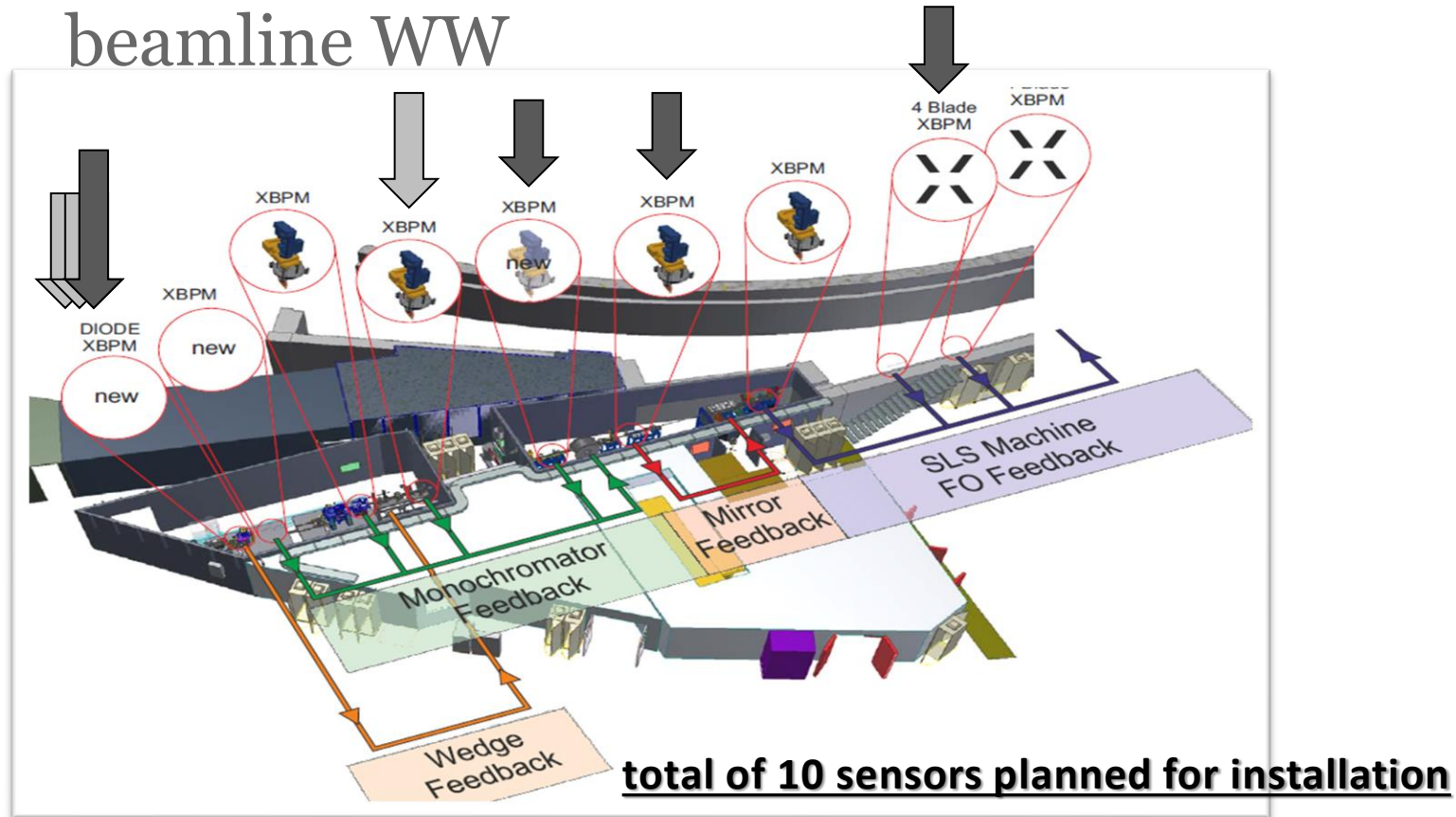


Schematic comparison of detectors

sensor type	Gas chambers	Blade monitors	Semiconductor sensors	fluorescence screen
transparency	high	very low very high	depends... 😊	low
radiation hardness	intrinsic high	medium/high	depends... 😊	low
foot print	medium/large	medium	extremely small 😊	large
lateral resolution	low	medium	very high 😊	medium
time response	low	low/medium	Very high 😊	low

- Can't we take best advantage of miniaturization
 - While mitigating the transparency/Rad-Hard responses?
- If so, solid state sensors will expand their areas of applications -**

microXAS@PSI currently represents the most advanced “XBPM-monitored” beamline WW

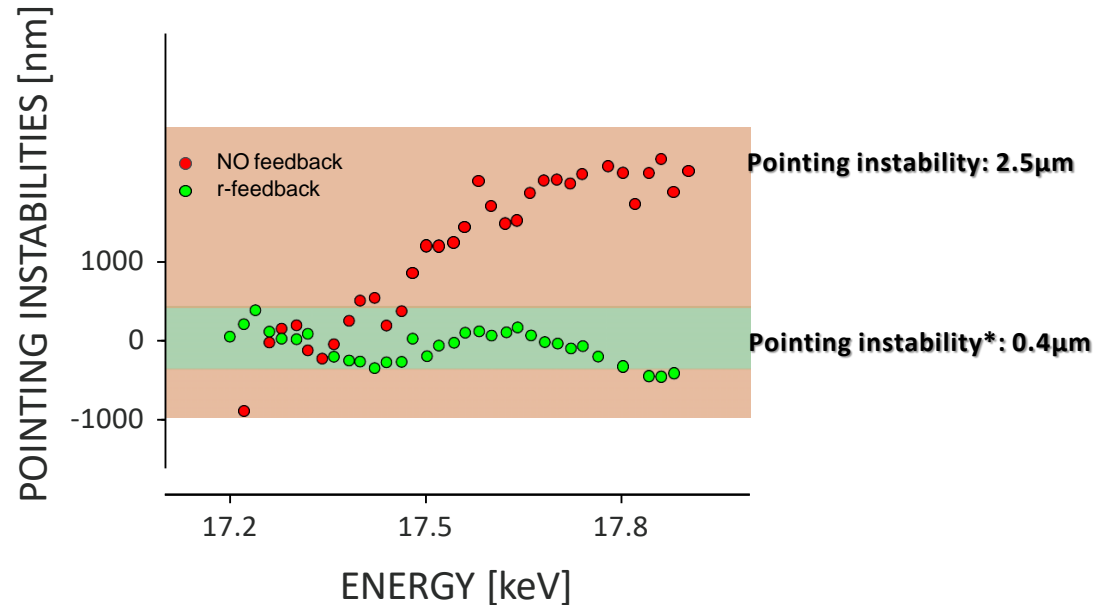


- **Currently installed:**
n.7 sensors (after mono, 10, nano-focus, pinkbeam and beam-stopper intensity)
- **Planned:** pixelated, before mono, whitebeam, beam-stopper position

massimo.camarda@SenSiC.ch

Monochromatic “standard” XBPM

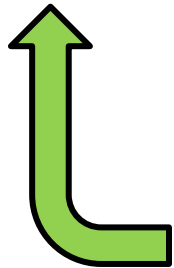
-first implemented SiC XBPM base feedback-loop schema



x5 Improvement using SiC XPBM based feedback system

Control/feedback important in spectroscopy measurements to compensate for energy drifts!

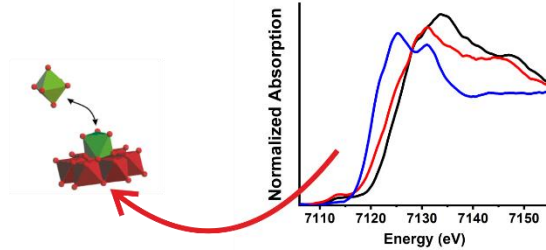
working on further automation/improvement



*sigma: <400nm

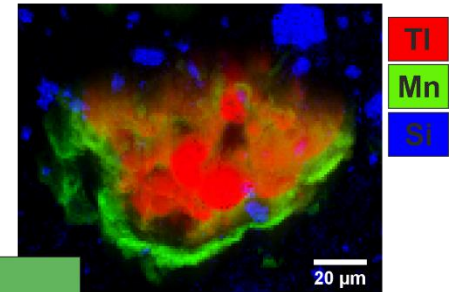
Near sample monitoring

-Beam stopper diode (no transmittance mode)

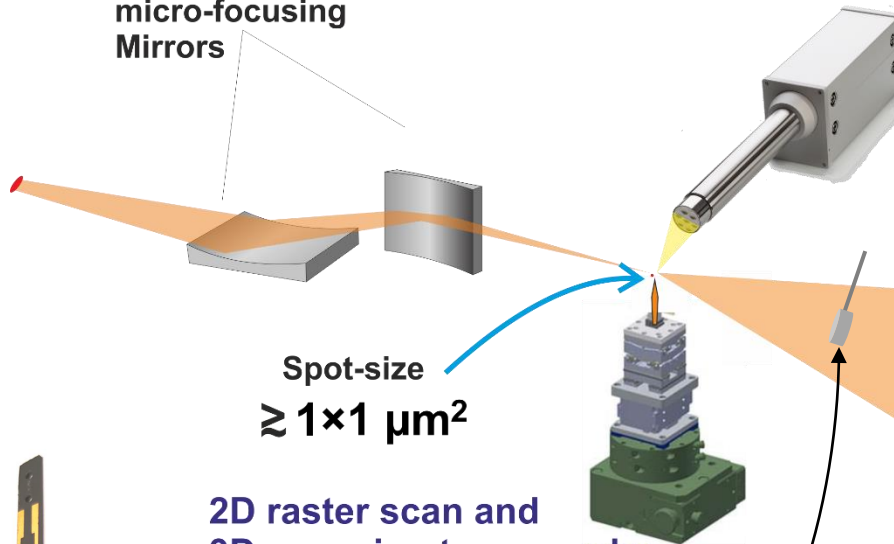


microscopic X-ray Absorption-Spectroscopies

- Oxidation state
- Chemical speciation
- Local atomic coordination

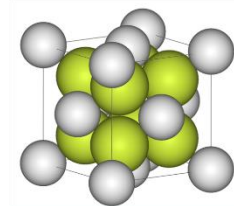


micro-focusing Mirrors



XRF detector

- Local element stoichiometry/composition



XRD detector

- Crystalline phase identification
- Chemical speciation
- Stress

2D raster scan and 3D scanning tomography

Absorption → SiC Diode on the beamstopper

- Absorption Contrast Imaging
- X-Ray Absorption Spectroscopy

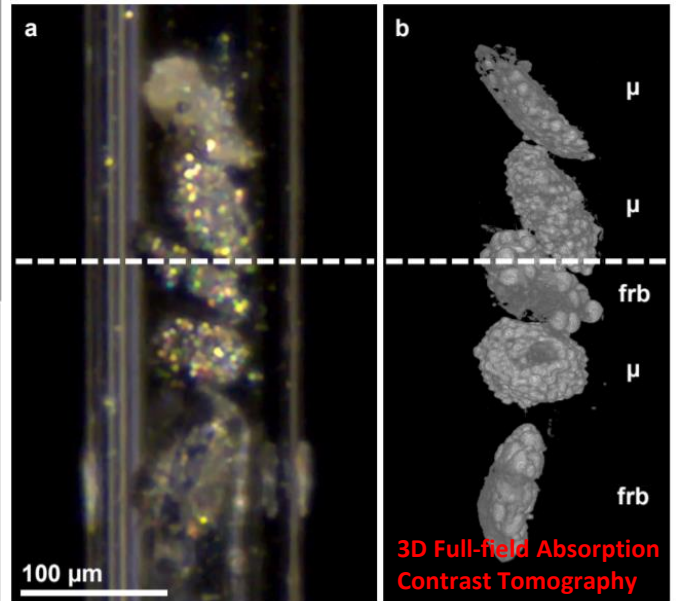
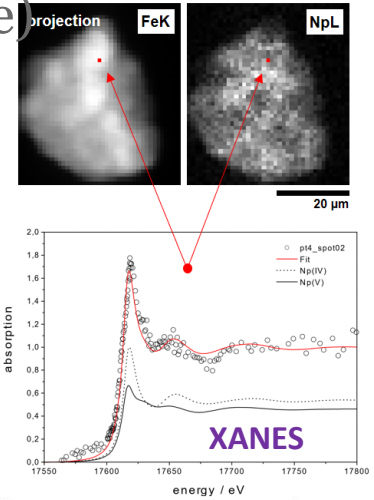
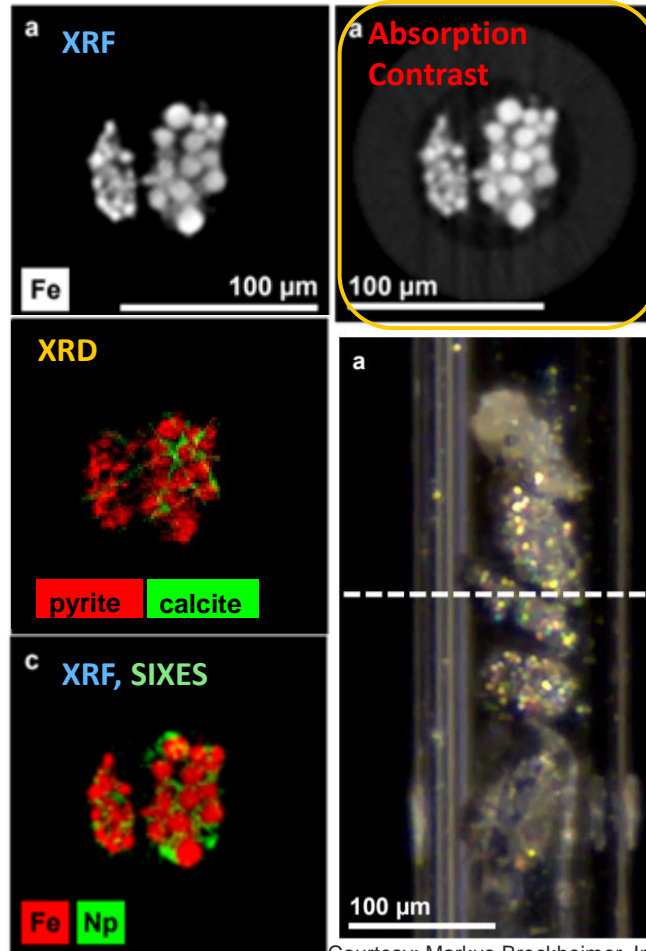
Collaboration of microXAS team with Massimo Camarda, Laboratory for Micro- and Nanotechnology, PSI

- 3D Mechatronic Integrated Device

da@SenSiC.ch

Near sample monitoring

-Beam stopper diode (no transmittance mode)

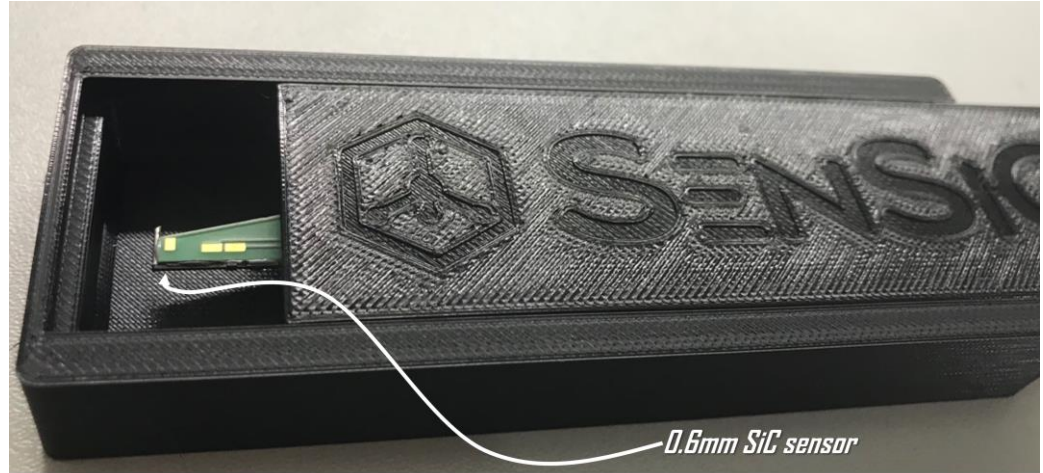


Courtesy: Markus Breckheimer, Institute for Nuclear Chemistry, Johannes Gutenberg-University Mainz

* massimo.camarda@SenSiC.ch

Near sample monitoring

-Beam stopper diode (no transmittance mode)

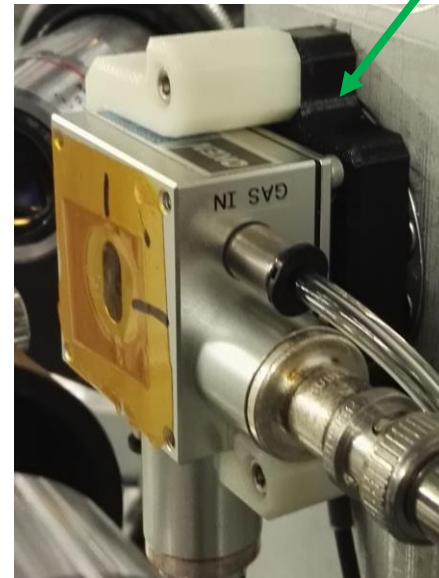


- **0.6mm (0.8mm) intensity monitor**
- **1.8mm (2mm) intensity monitor**
- **1.8mm (2.2mm) position monitor**
- **2.8mm (3.3mm) position monitor**

*[*massimo.camarda@SenSiC.ch](mailto:massimo.camarda@SenSiC.ch)*

Near sample monitoring

-Fast/compact intensity sensor*



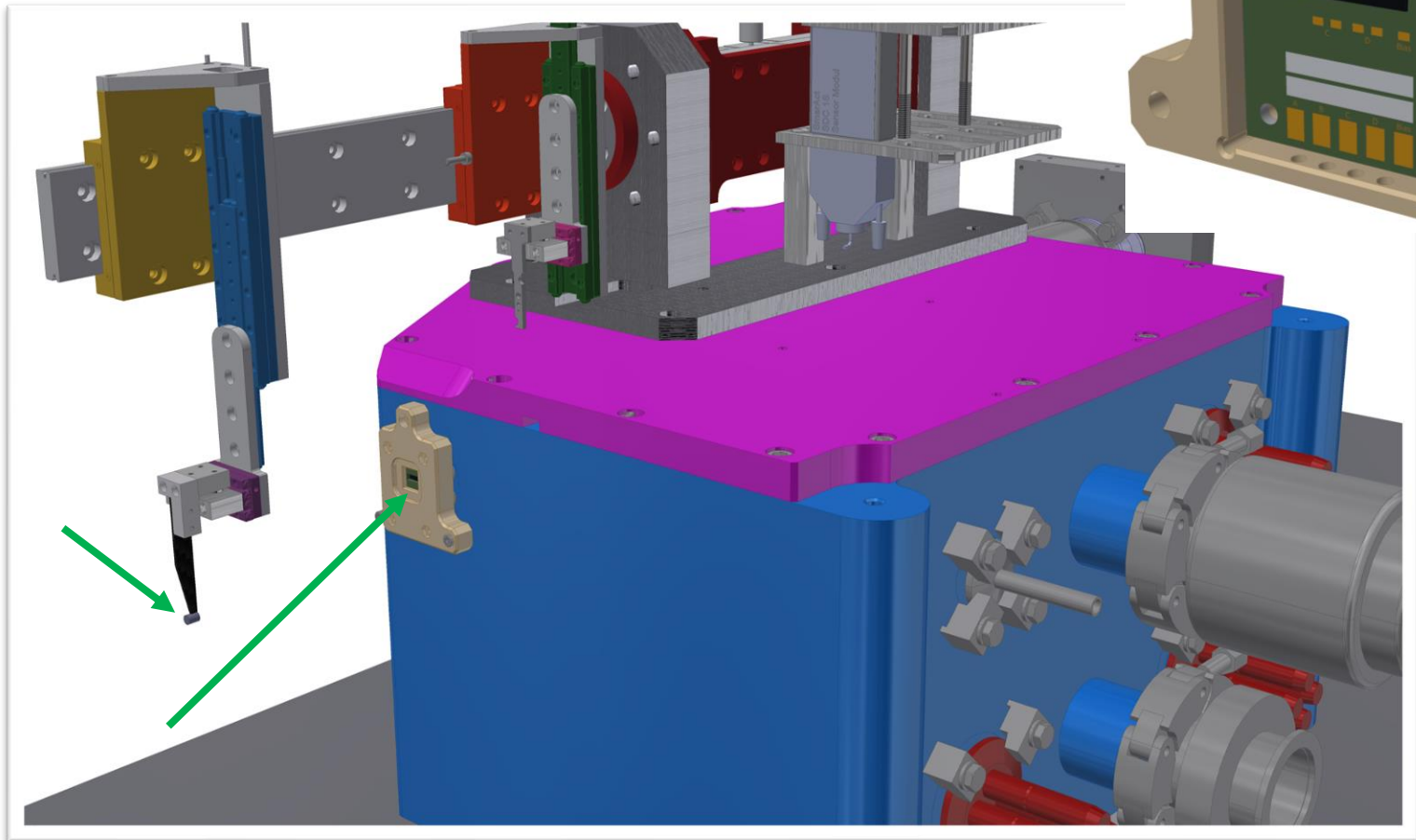
CURRENTLY WORKING ON:

1. COMBINATION OF INTENSITY+POSITION MONITOR (TELESCOPE CONFIG.)
2. COMBINATION OF POSITION + PIN-HOLE

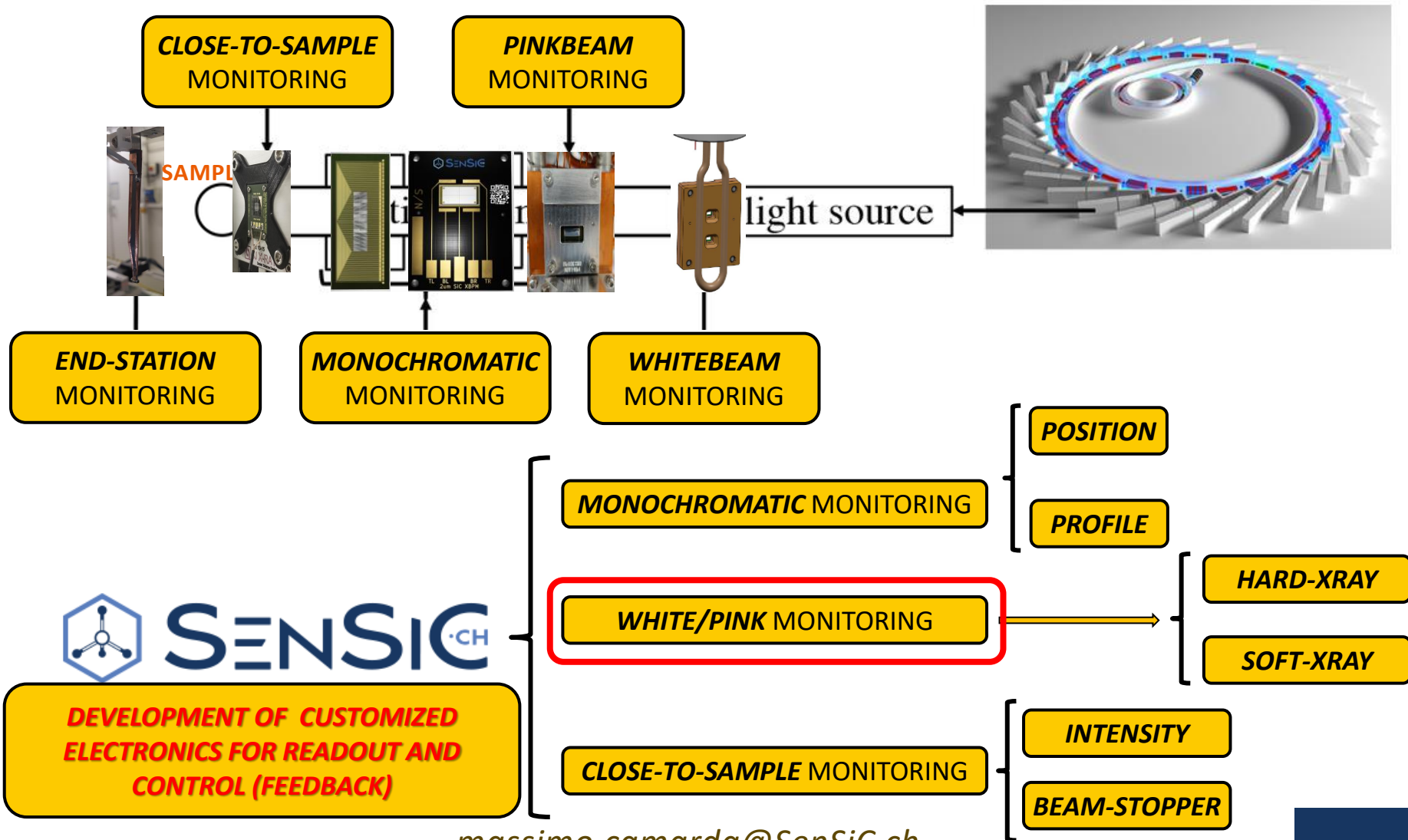
massimo.camarda@SenSiC.ch

Near sample monitoring

-Fast/compact intensity sensor*

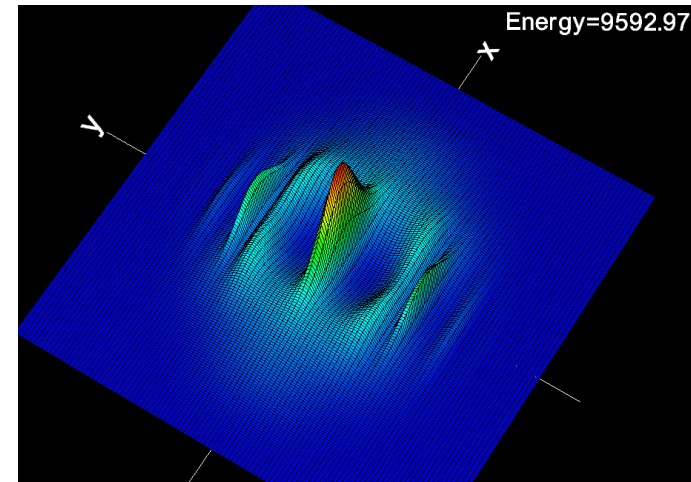
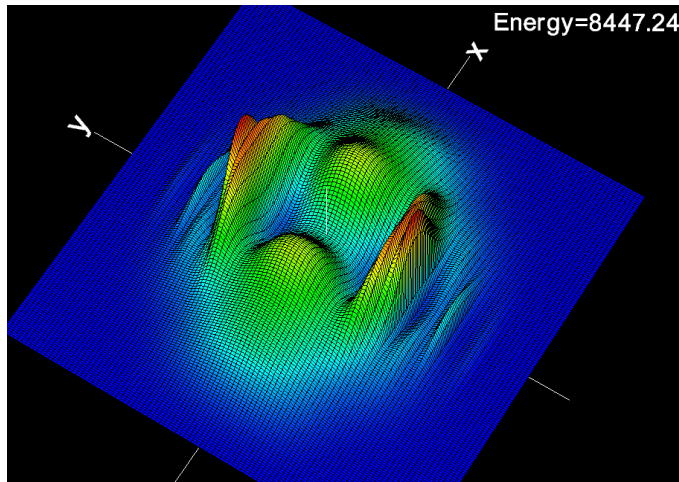
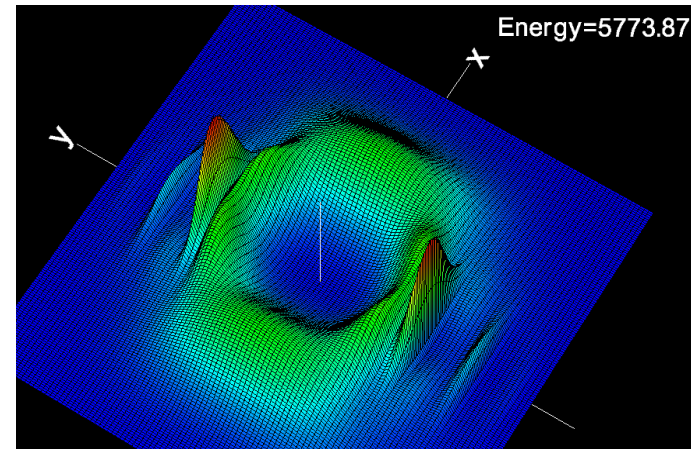
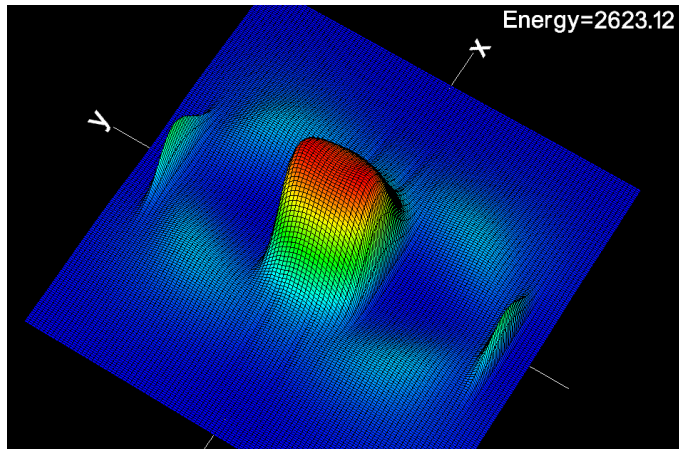


Value proposition



ID whitebeam, spectra (microXAS, spectra)

1. determine flux(E,x,y,z) generated by ID (Spectra)



plots using very wide acceptance window (24x24mm²)

ID whitebeam, spectra (microXAS, spectra)

1. determine flux(E,x,y,z) generated by ID (Spectra)

SPECTRA 10.2 - C:\Users\Massimo\Dropbox\191017 PSI\OTHER\DEVELOPMENTS\Console... - □ ×

File Select Calculation Run Utility Configuration Help

Accelerator Specification

Storage Ring

Bunch Profile: **Gaussian** Injection Condition: **Default**

Electron Energy (GeV)	2.411	Energy Spread	0.8784e-3		
Average Current (mA)	400	β_x (m)	8.32	α_x	-2.1
Circumference	300	β_y (m)	0.52	α_y	0.007
Bunches	400	η_x (m)	0	η_x'	0
σ_z (mm)	6	η_y (m)	0	η_y'	0
Peak Current (A)	19.9471	$1/\gamma$ (mrad)	0.211945		
Natural Emittance (m.rad)	56.3e-10	σ_x (mm)	0.2162	σ_x' (mrad)	0.06045
Coupling Constant	0.00178	σ_y (mm)	2.281e-03	σ_y' (mrad)	4.386e-03
ϵ_x (m.rad)	5.62e-09	$\gamma\sigma_x'$	0.2852	$\gamma\sigma_y'$	0.02069
ϵ_y (m.rad)	1.000e-11				

Light Source Description

Linear Undulator

Link Gap & Field Segmented Undulator
 End Correction Magnets Symmetric Profile

Gap Value	24	σ_r (mm)	4.481e-03	σ_r' (mrad)	0.01611
B(T)	0.845506	Σ_x (mm)	0.2163	Σ_x' (mrad)	0.06256
Periodic Length (cm)	1.9	Σ_y (mm)	5.028e-03	Σ_y' (mrad)	0.01669
Device Length (m)	1.8	λ_{1st} (nm)	0.906835		
Regular Magnet Length (m)	1.748	ϵ_{1st} (peak:eV)	1363.12		
Number of Regular Periods	92	ϵ_{3rd} (peak:eV)	4096.47		
K Value	1.5	Flux _{1st}	2.0206e+15		
ϵ_{1st} (eV)	1367.22	Brilliance _{1st}	4.5073e+19		
		Peak Brilliance	2.24769e+21		
		Bose Degeneracy	0.698894		
		Total Power (kW)	1.83832		

Scan Configuration ×

Logarithmic Step?

Scan Fixed Energy (eV)

Initial Value

Final Value

Number of Points

Interval or Gain/Step

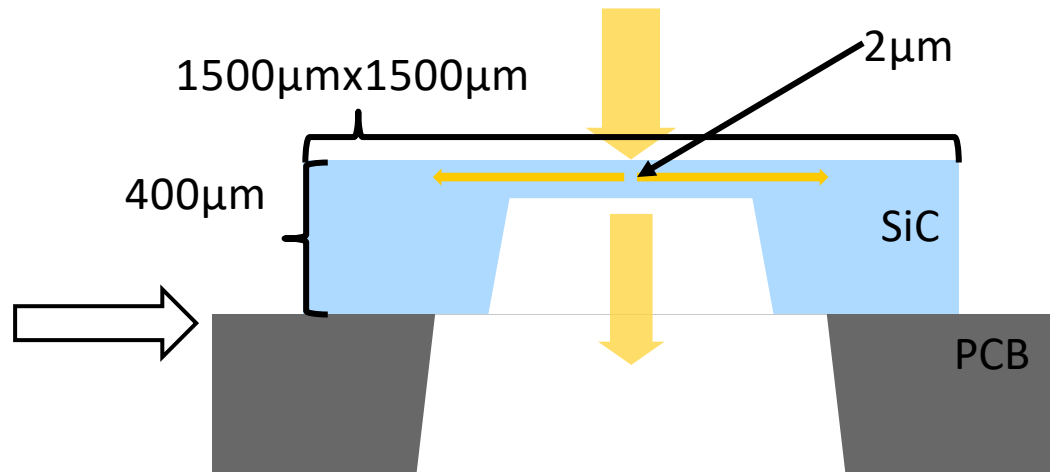
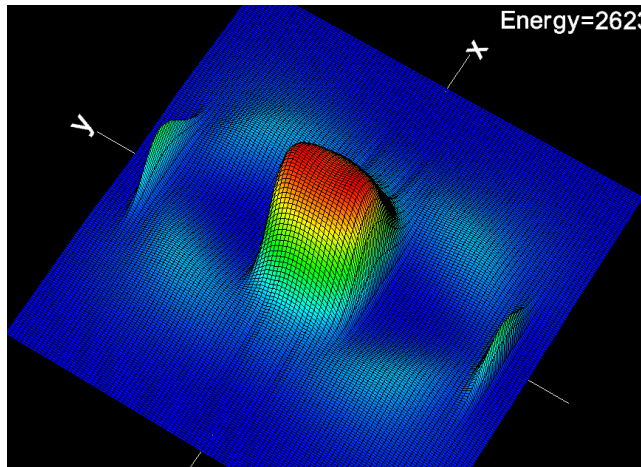
Initial Serial #

OK CANCEL

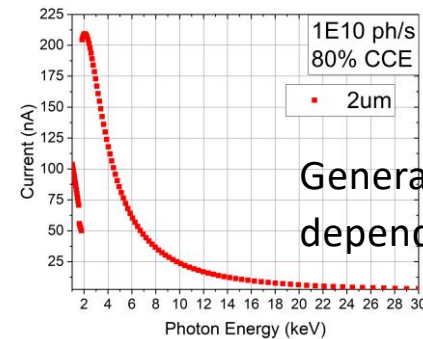
ID whitebeam, spectra (microXAS, spectra)

2. determine current on XBPM

Flux after optical elements



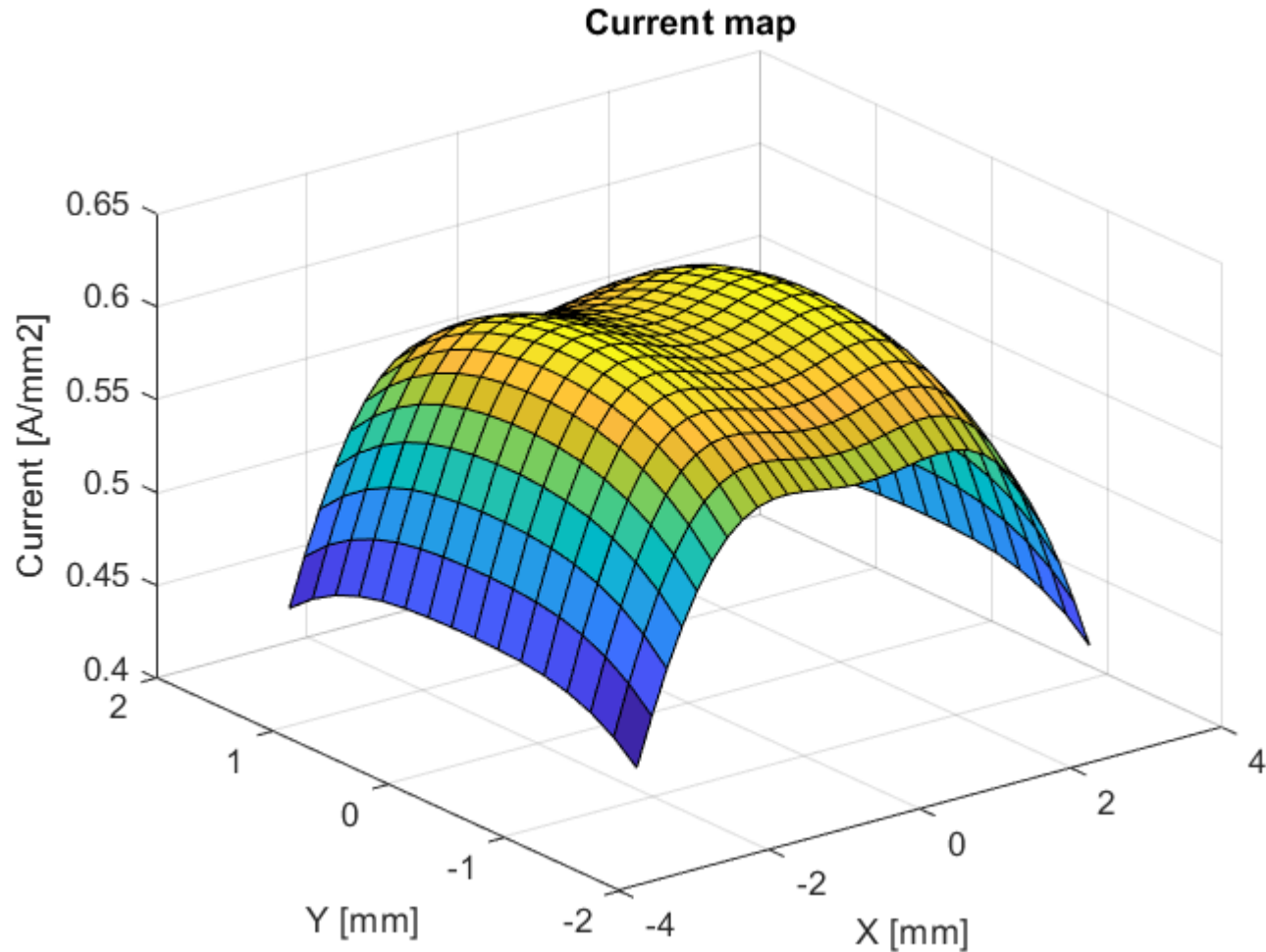
(X,Y,E) CURRENT MAPS ←



Generated current depends on E_{ph}

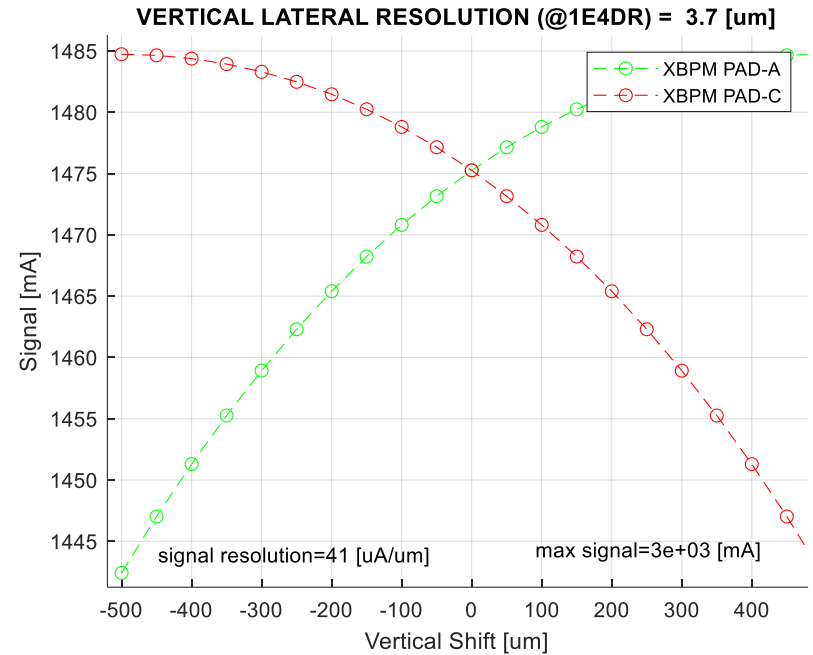
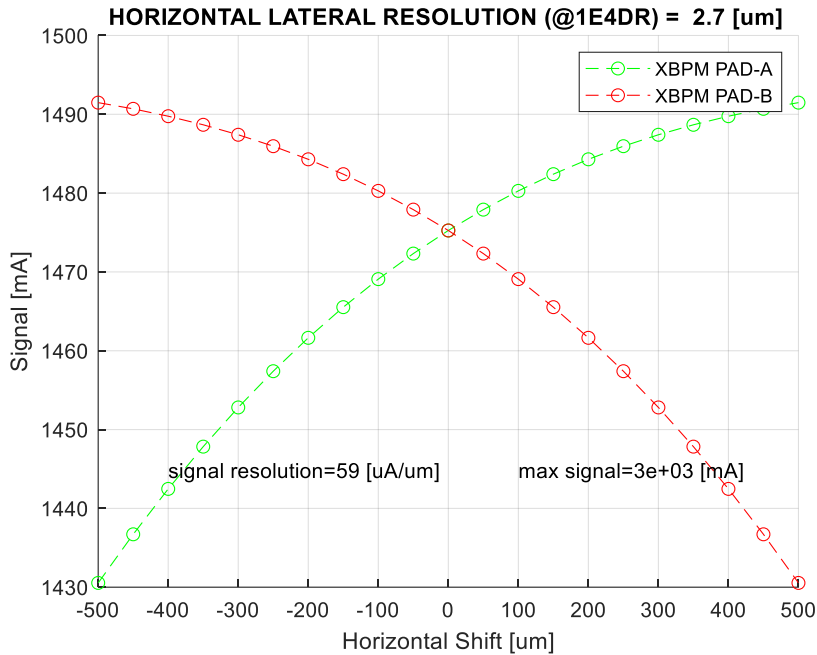
Beam to Current conversion

“Standard 2 μ m SiC XBPM, microXAS”



Knife-edge scan at center

Standard 2um SiC XBPM@microXAS

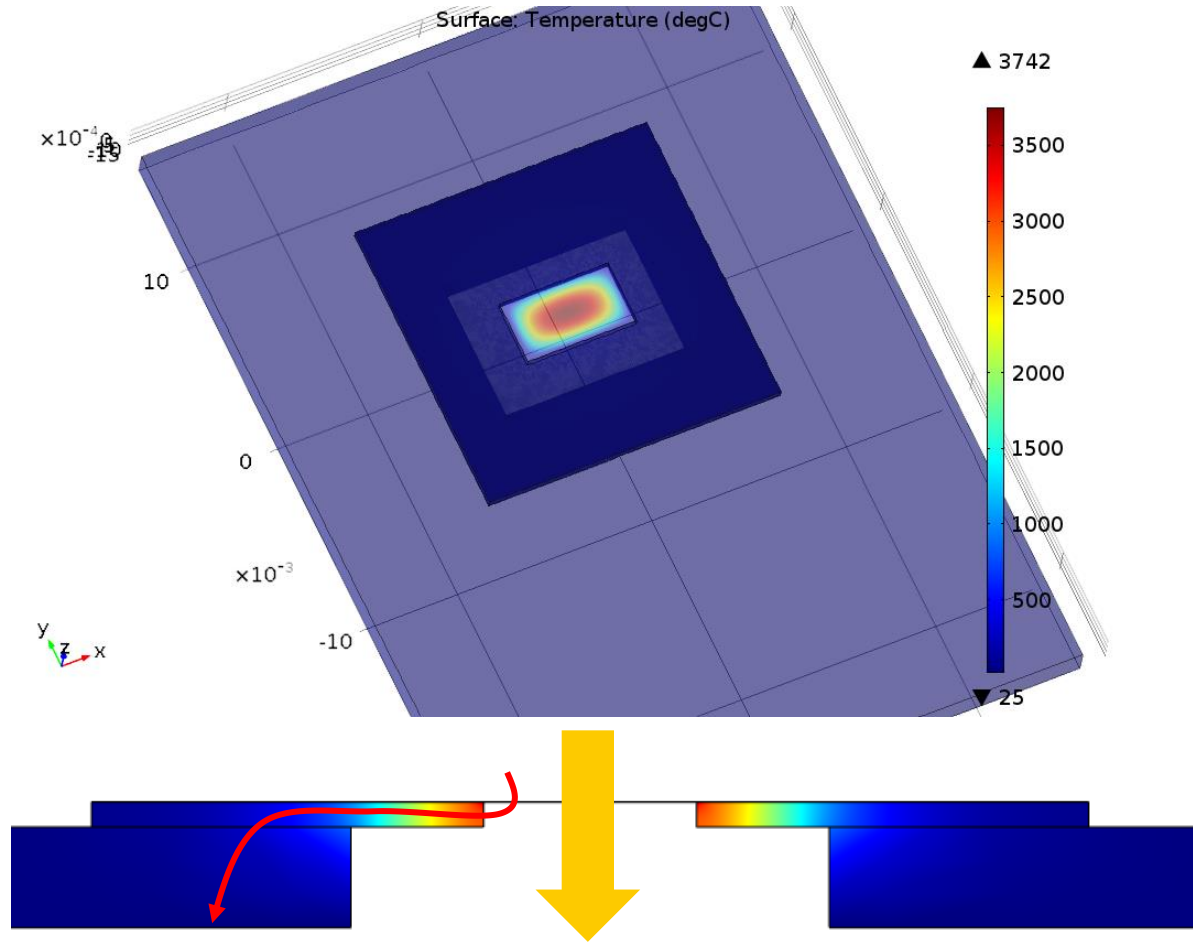


(Theoretical) lateral resolution of [2.7um,3.7um]

Max current on device (diaphragm*) 3[A]

Temperature profile

Standard 2um SiC XBPM@microXAS



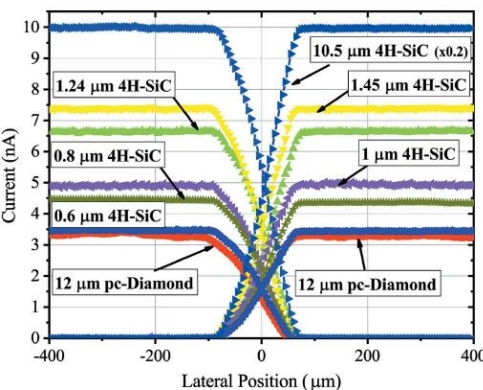
Expected 3500°C....

massimo.camarda@SenSiC.ch

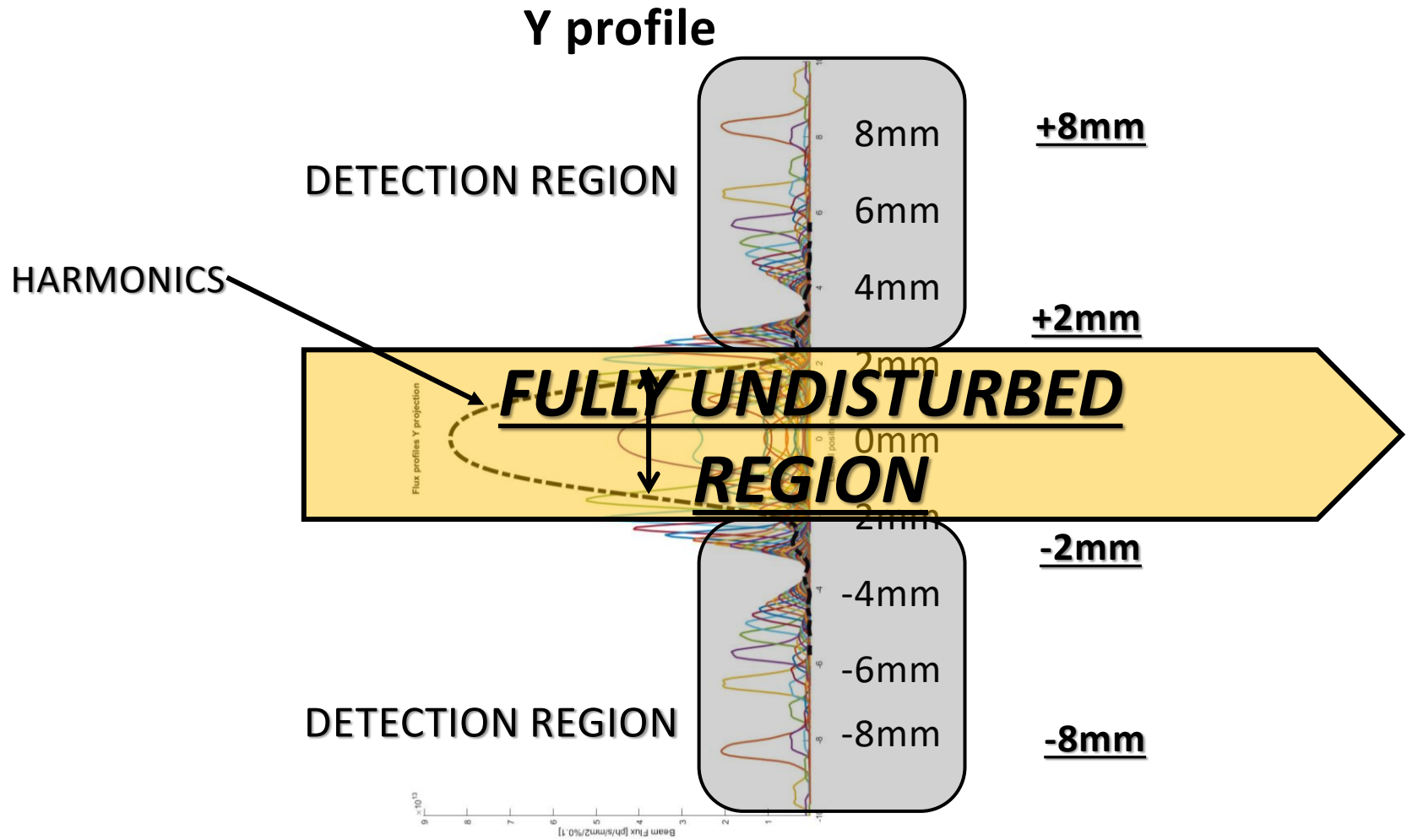
Silicon carbide X-ray beam position monitors for synchrotron applications

Selamness Nida,^{a,*} Alexander Tsibizov,^a Thomas Ziemann,^a Judith Woerle,^{a,b}
 Andy Moesch,^c Clemens Schulze-Briese,^c Claude Pradervand,^b Salvatore Tudisco,^d
 Hans Sigg,^b Oliver Bunk,^b Ulrike Grossner^a and Massimo Camarda^{a,b,*}

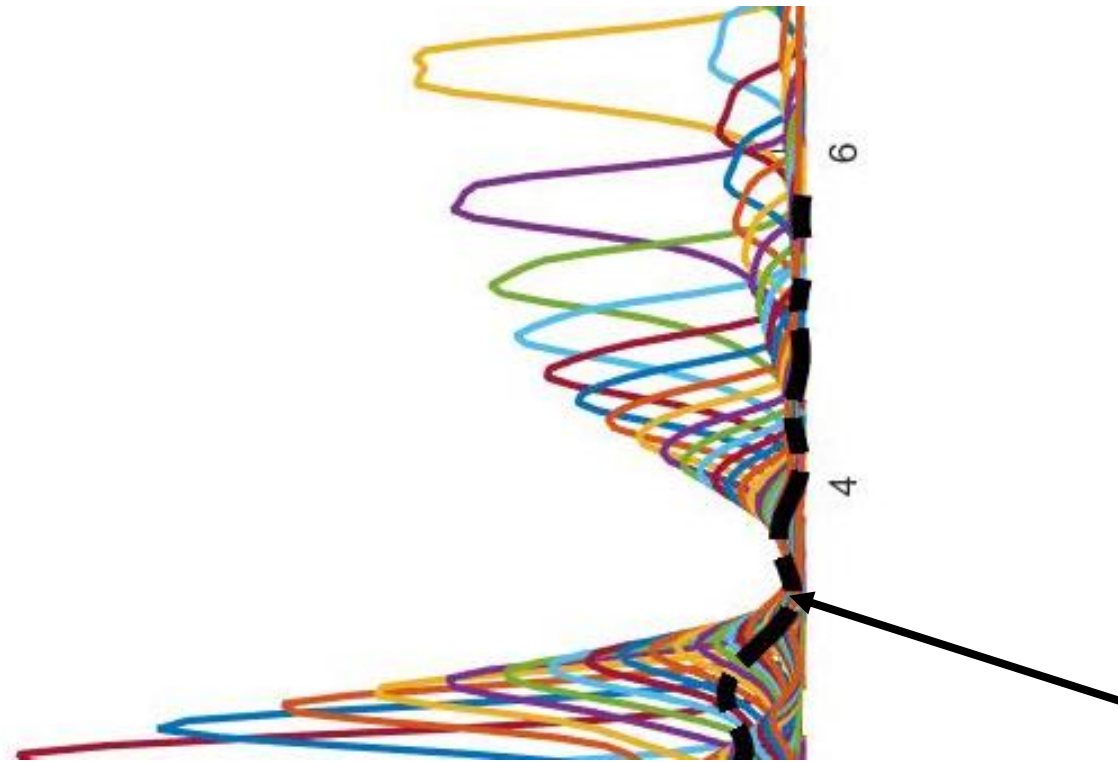
In this work, the performance of thin silicon carbide membranes as material for radiation hard X-ray beam position monitors (XBPMs) is investigated. Thermal and electrical behavior of XBPMs made from thin silicon carbide membranes and single-crystal diamond is compared using finite-element simulations. Fabricated silicon carbide devices are also compared with a 12 μm commercial polycrystalline diamond XBPM at the Swiss Light Source at the Paul Scherrer Institute. Results show that silicon carbide devices can reach equivalent transparencies while showing improved linearity, dynamics and signal-to-noise ratio compared with commercial polycrystalline diamond XBPMs. Given the obtained results and availability of electronic-grade epitaxies on up to 6 inch wafers, it is expected that silicon carbide can substitute for diamond in most beam monitoring applications, whereas diamond, owing to its lower absorption, could remain the material of choice in cases of extreme X-ray power densities, such as pink and white beams.



Generalities of whitebeam monitoring



Generalities of whitebeam monitoring

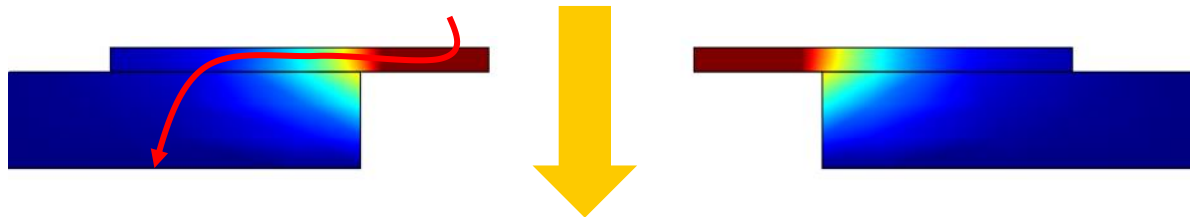
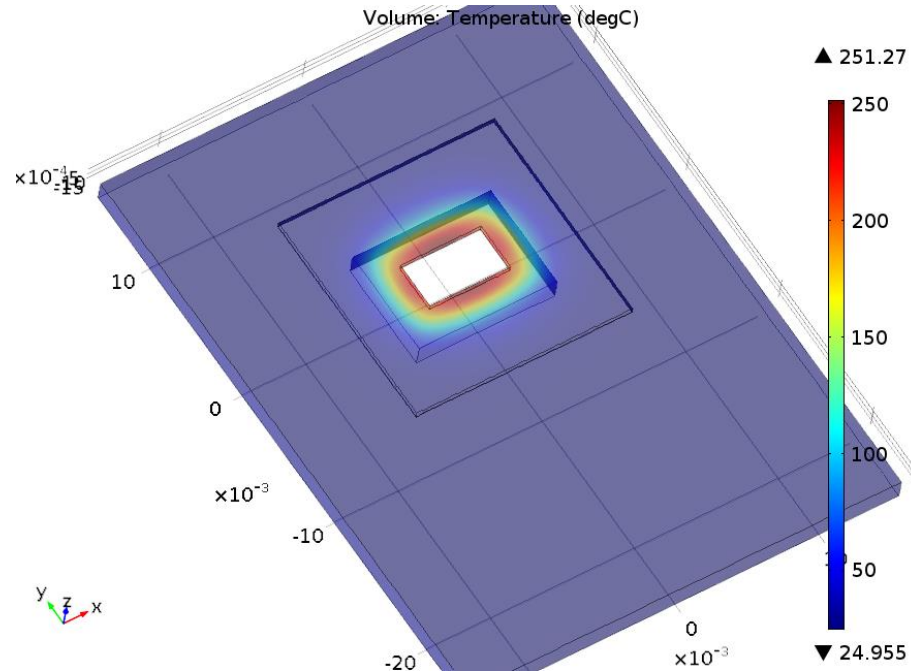


WE ARE NOT MEASURING THE «TAILS» OF THE BEAM

WE ARE REALLY MEASURING THE «OFF HARMONIC» COMPONENTS!

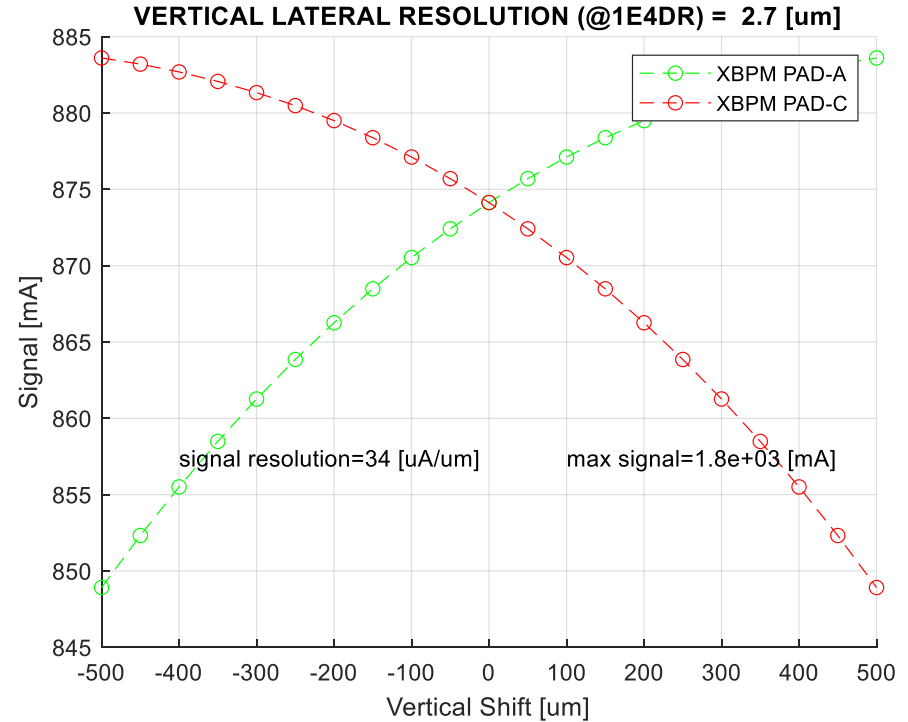
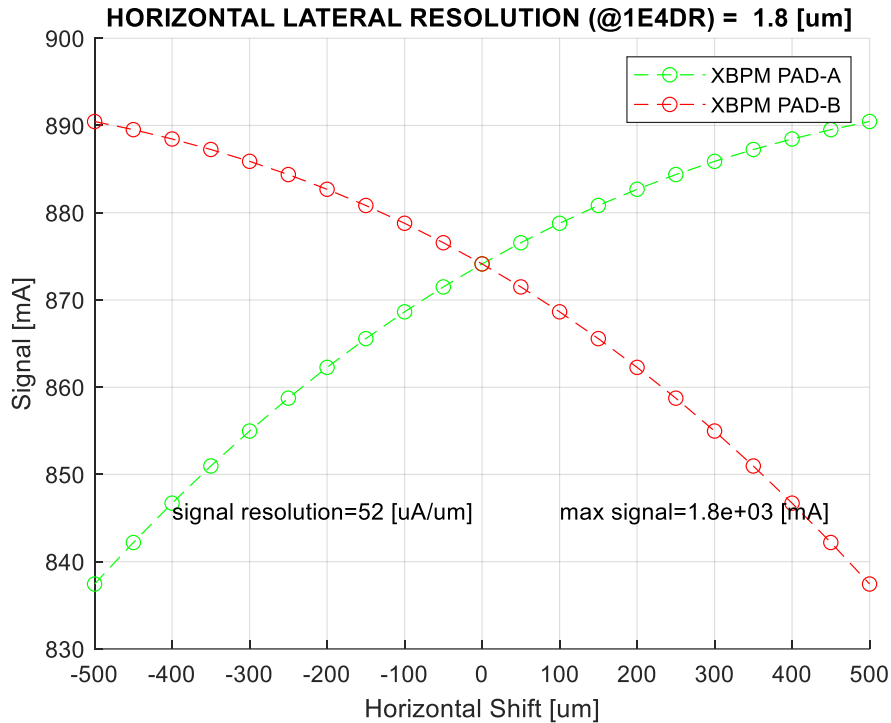
CROSS-CHROMATIC MONITORING

Whitebeam monitoring “Blade-type” 2 μ m SiC XBPM, microXAS



SIMULATED TEMPERATURE: 250°C (x10 reduction!)

Knife-edge scan at center “Blade-type” 2um SiC XBPM, microXAS



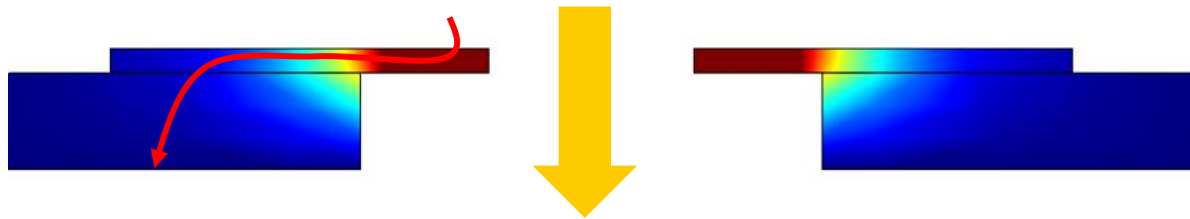
Max current on device (diaphragm) 1.7[A] (x2 reduction)

Whitebeam monitoring

“Blade-type” 2 μ m SiC XBPM@microXAS

- Max current on device (diaphragm) **1.7[A] (x2 reduction)**

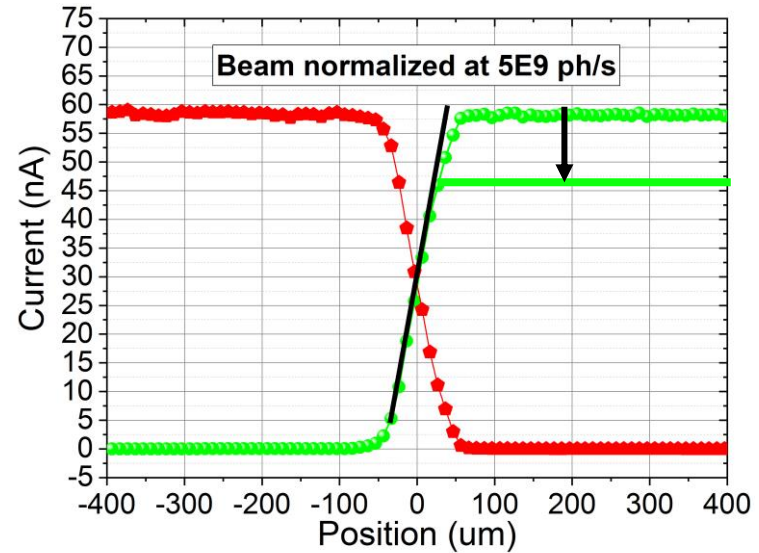
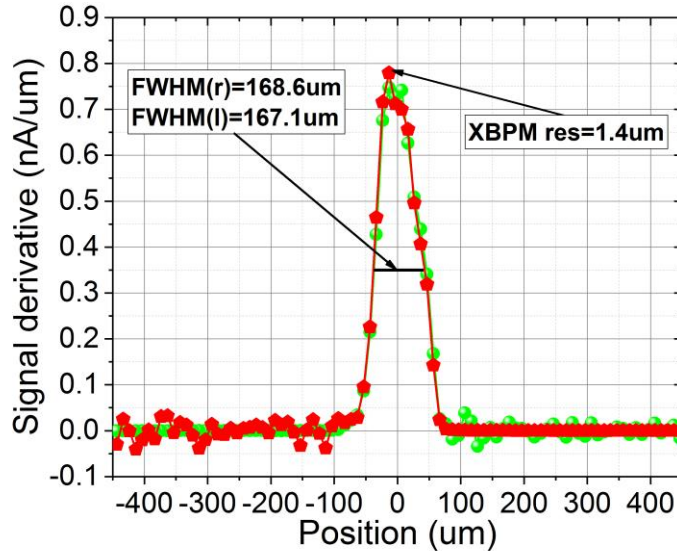
- Max temperature **250°C (x10 reduction)**



- Lateral resolution of **[1.8 μ m, 2.7 μ m] (\approx x2 improvement)**

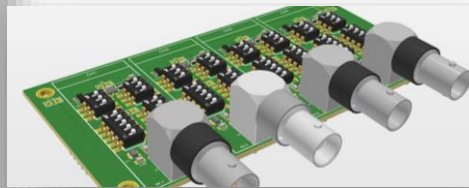
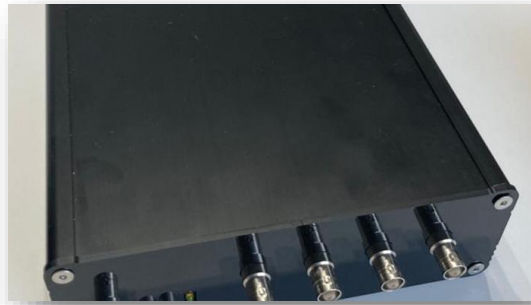
Whitebeam monitoring

“Blade-type” 2um SiC XBPM@microXAS



LATERAL RESOLUTION

$$\frac{\text{Max current}}{\nabla \text{current}(x, y) / \nabla x} \times \frac{1}{\text{SNR}(\text{electronics})}$$



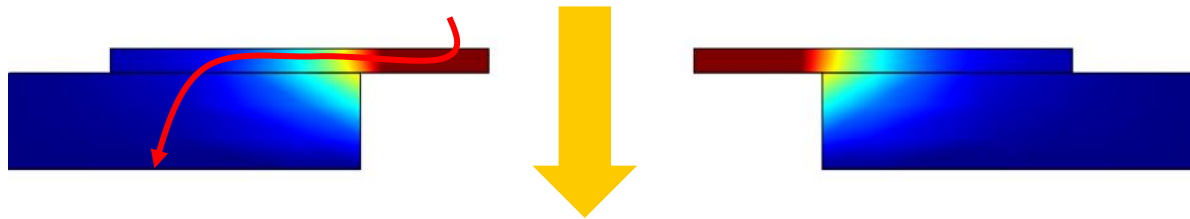
$$\text{SNR}(\text{electronics}) \approx 1E4$$

Whitebeam monitoring

“*Blade-type*” 2 μ m SiC XBPM@microXAS

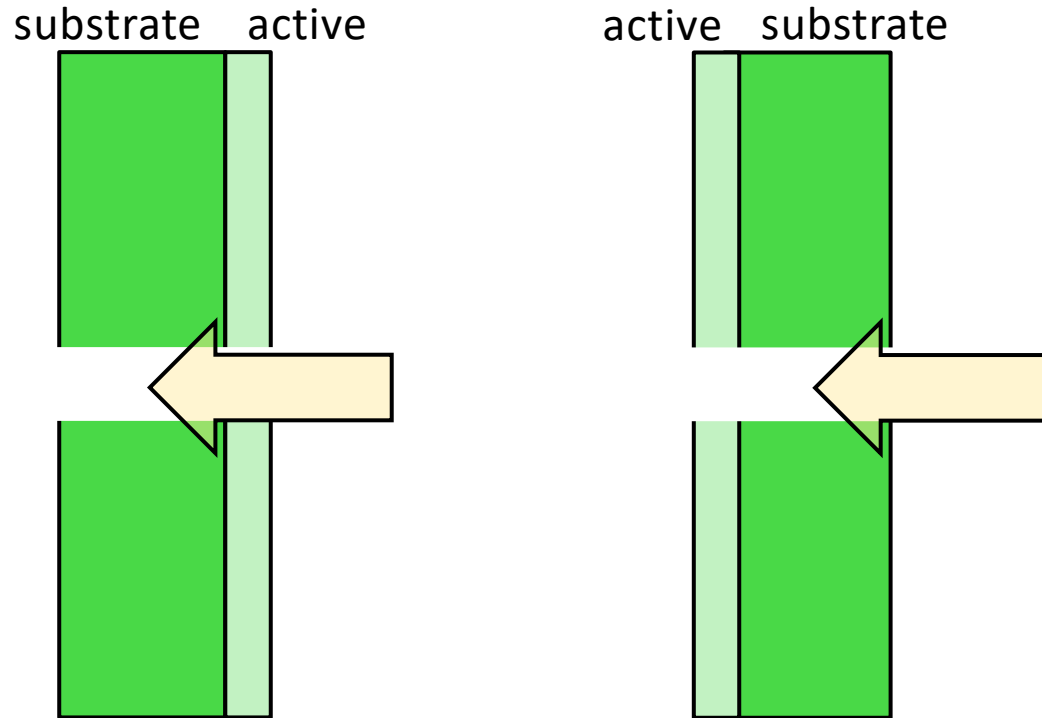
- Max current on device (diaphragm) 1.7[A] (x2 reduction) ←

- Max temperature 250°C (x10 reduction)



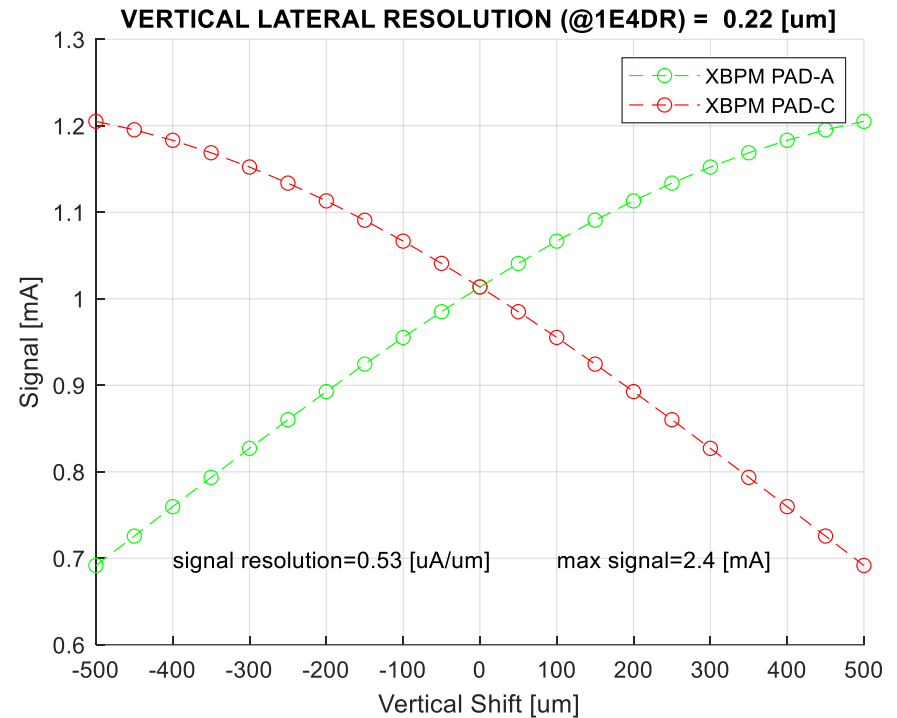
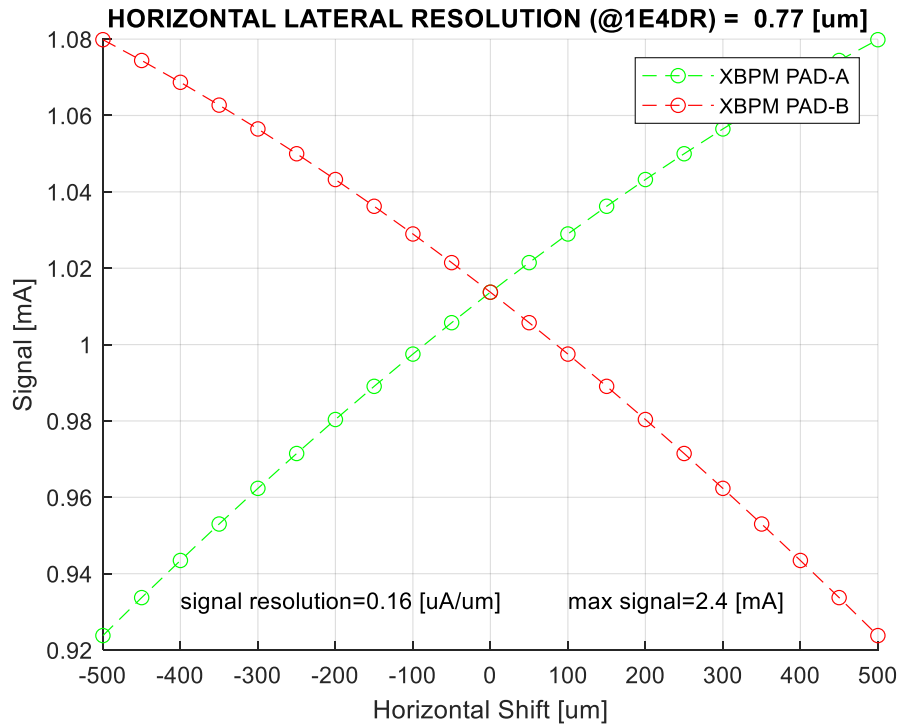
- Lateral resolution of [1.8 μ m, 2.7 μ m] (\approx x2 improvement)

Response of SiCBlades: FILTERED CONFIGURATION



- we are using an *“integrated/monolithic/local filter”*
- quite strong filter (*equivalent to 3.6mm diamond window*)
- a filter present only on the tails, not at beam center
 - applicable for all Xray beamlines (soft-hard)

Whitebeam monitoring “OPTIMIZED Blade-type” 2um SiC XBPM, microXAS

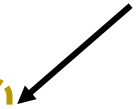


Max temperature same of before (250°C)...

Max current on device (diaphragm) 2 [mA] (>x1000 reduction)

Lateral resolution of [0.7um,0.22um] (>x3-10 improvement*)

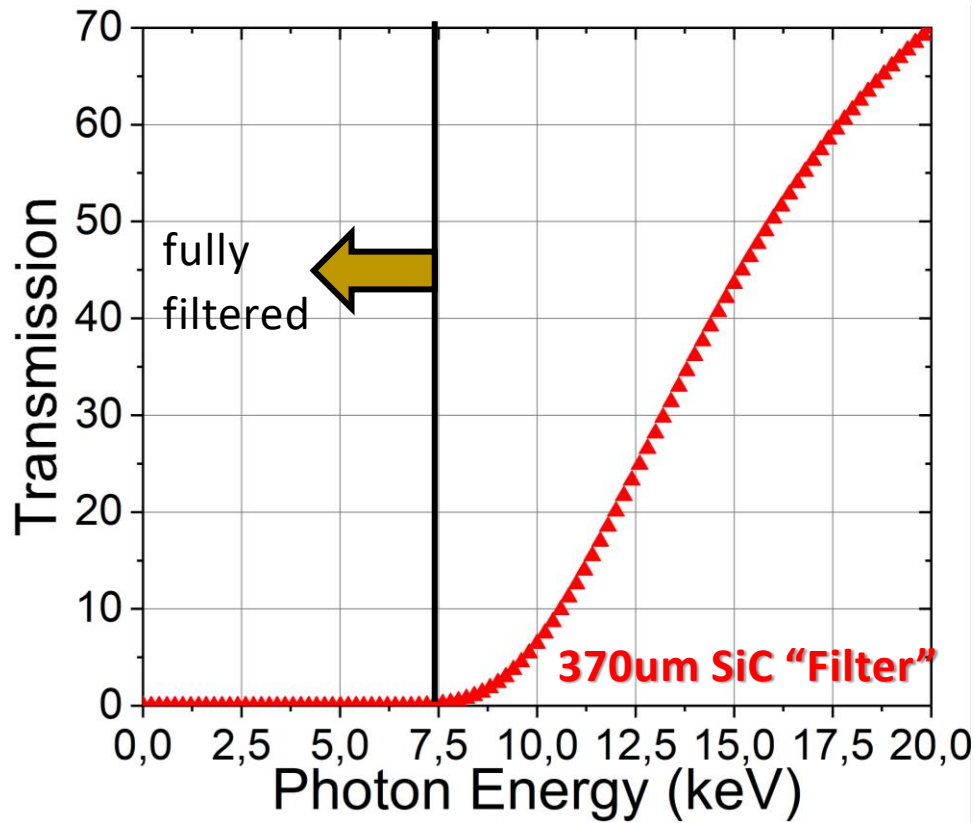
WHY???



2um mem= [2.7um,3.7um]
blade=[1.8um,2.7um]

massimo.camarda@SenSiC.ch

Blade-type sensors: OPTIMIZED

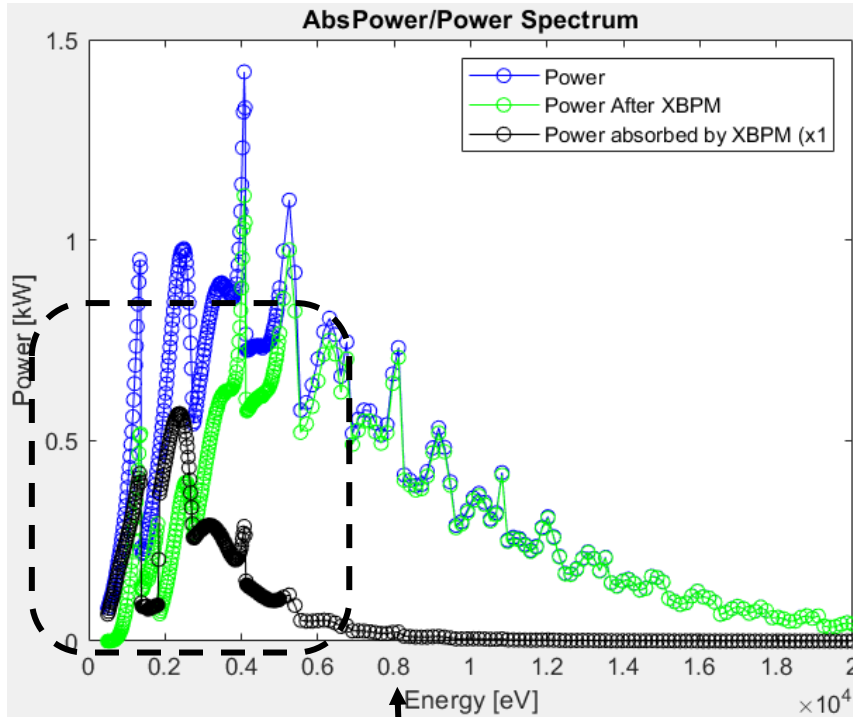


filtering everything below 7.5keV → cross-chromatic monitoring

filtering everything below 7.5keV → can filter bendig magnet radiation

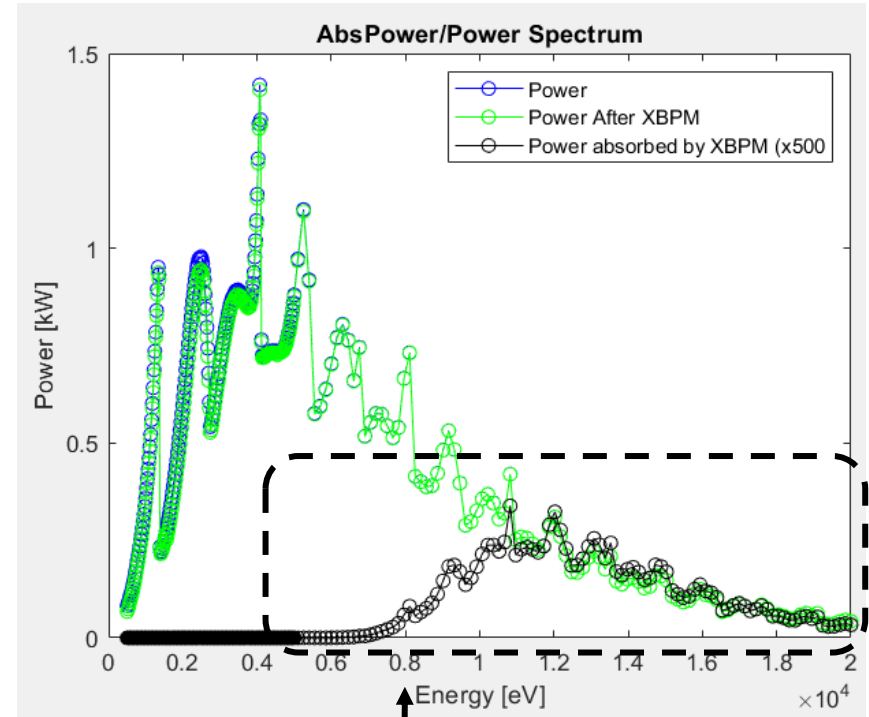
Blade-type sensors: OPTIMIZED

STANDARD SiC XBPM



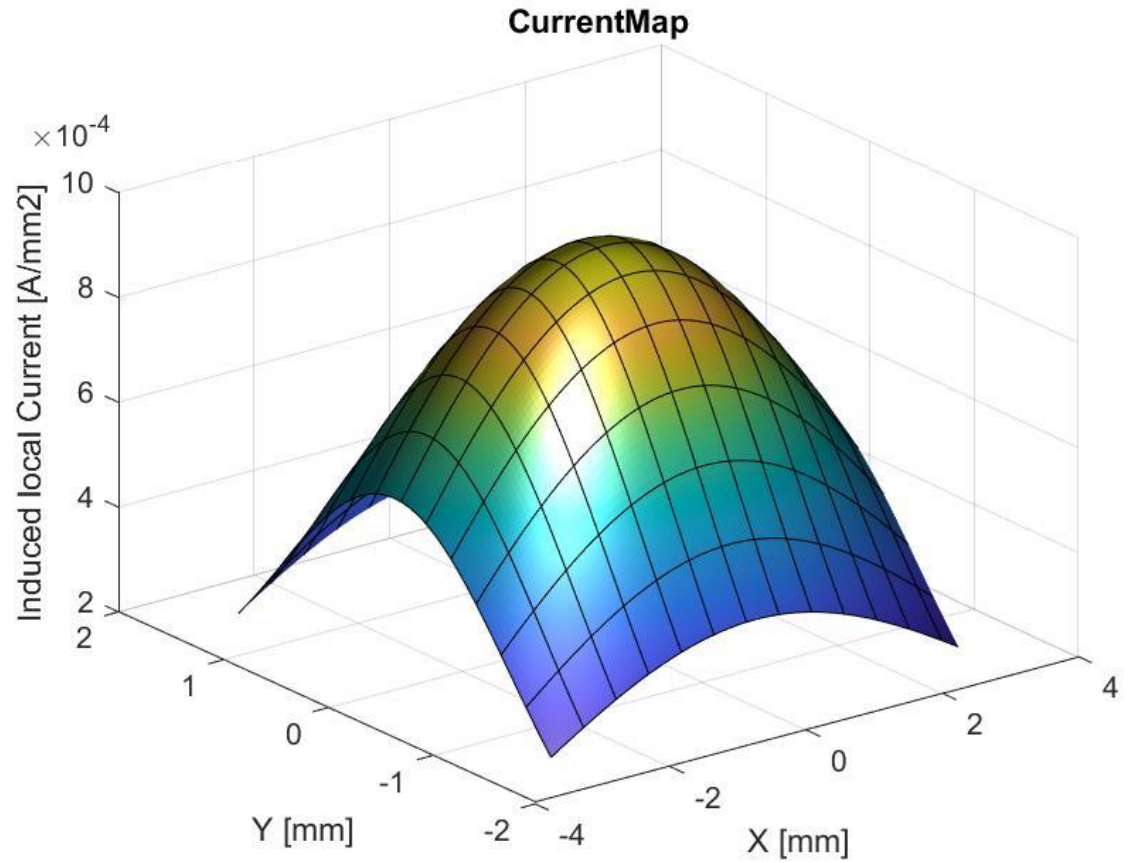
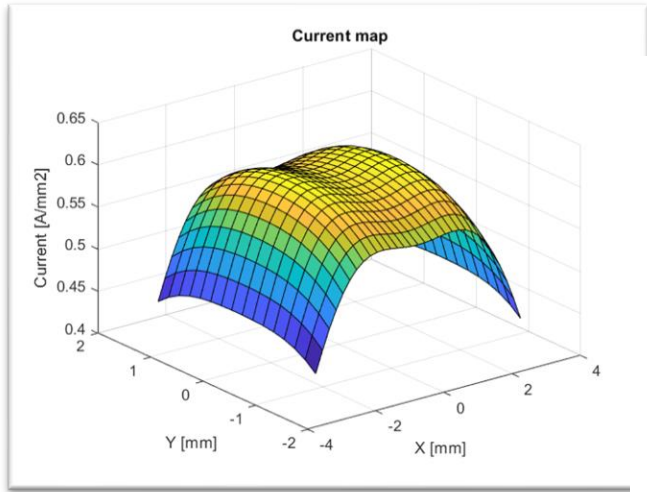
main signal contribution
coming from <8keV photons

OPTIMIZED SiC XBPM



main signal contribution
coming from <8keV photons

STD vs. FLIPPED



Knife-edge scan at center comparison of XBPM types @ SIM beamline

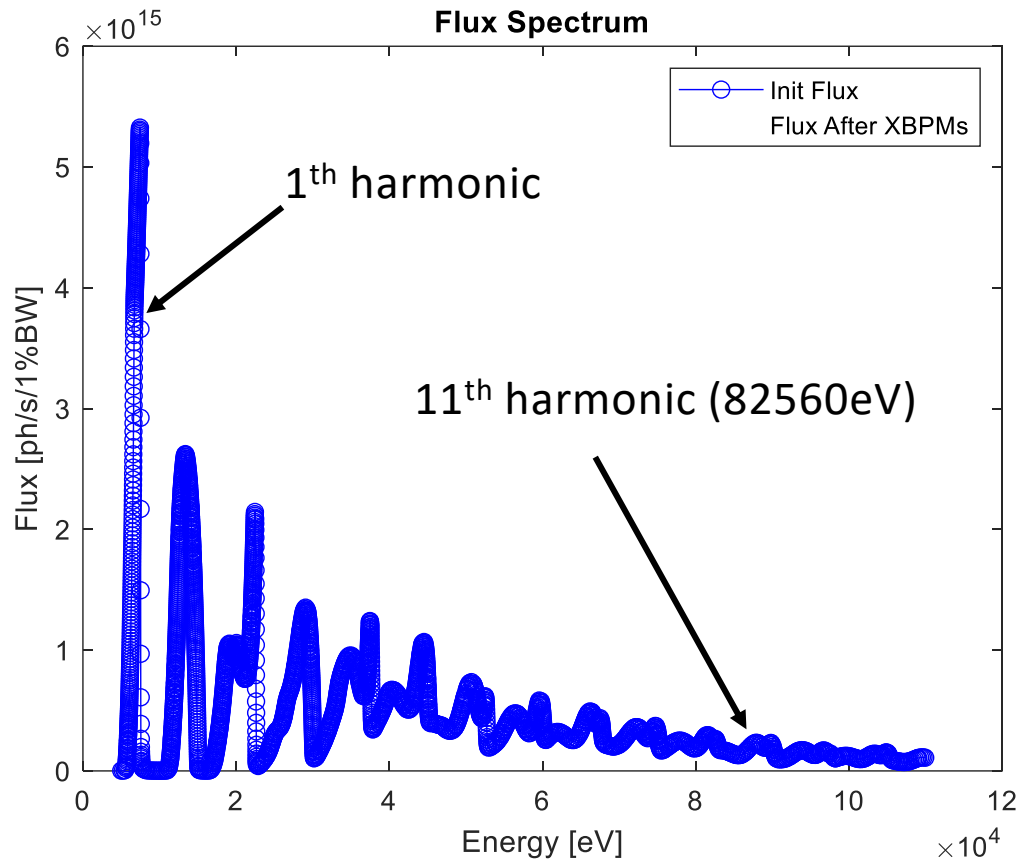
- | | | |
|-----------------------------------|---|---|
| “Standard” 2um SiC XBPM | { | <ul style="list-style-type: none"> • Lateral resolution of [116um(!)– 1.3um] • Max current on device 4.8[A] • Max temperature 3000°C |
| “BLADE” SiC XBPM | { | <ul style="list-style-type: none"> • Lateral resolution of [138um– 0.86um] • Max current on device 1.4[A] • Max temperature 130°C! |
| “OPTIMIZED BLADE” SiC XBPM | { | <ul style="list-style-type: none"> • Lateral resolution of [<u>4.6um(!)– 0.18um</u>] • Max current on device 1[mA] • Max temperature 130°C |
- [x25(!)–x7]**

SPECTRA parameters/calculations

B1 Engineering materials beamline@HEPS

Accelerator		Light Source	
Storage Ring ▼		Linear Undulator ▼	
Energy (GeV)	6	B (T)	
Current (mA)	200	λ_U (mm)	
Circumference (m)	1360.4	Device Length (m)	
Bunches	680	Reg. Magnet Length (m)	3.9078
σ_z (mm)		# of Reg. Periods	234
Nat. Emittance (m.rad)		K value	1.8556
Coupling Constant		ϵ_{1st} (eV)	7521.66
Energy Spread		$\sigma_{r,r'}$ (mm,mrad)	2.856e-3, 4.592e-3
$\beta_{x,y}$ (m)		$\Sigma_{x,x'}$ (mm,mrad)	9.292e-3, 5.549e-3
$\alpha_{x,y}$	0, 0	$\Sigma_{y,y'}$ (mm,mrad)	3.665e-3, 4.746e-3
$\eta_{x,y}$ (m)	0, 0	λ_{1st} (nm)	0.164836
$\eta'_{x,y}$	0, 0	Flux _{1st}	2.84123e+15
Peak Current (A)	4.98825	Brilliance _{1st}	8.02252e+22
$\epsilon_{x,y}$ (m.rad)	2.755e-11, 2.755e-12	Peak Brilliance	2.00091e+24
$\sigma_{x,y}$ (mm)	8.842e-3, 2.297e-3	Bose Degeneracy	3.73659
$\sigma'_{x,y}$ (mrad)	3.115e-3, 1.199e-3	Total Power (kW)	25.2087
γ^{-1} (mrad)	0.0851665	Gap-Field Relation	None ▼
Bunch Profile	Gaussian ▼	Field Structure	Antisymmetric ▼
<input type="checkbox"/> Zero Emittance		<input checked="" type="checkbox"/> End Correction Magnet	
<input type="checkbox"/> Zero Energy Spread		Natural Focusing	None ▼
		<input type="checkbox"/> Field Offset & Taper	
		<input type="checkbox"/> Add Phase Error	
		Segmentation	None ▼

Integrated (over *space*, assuming 0.1%BW) FLUX

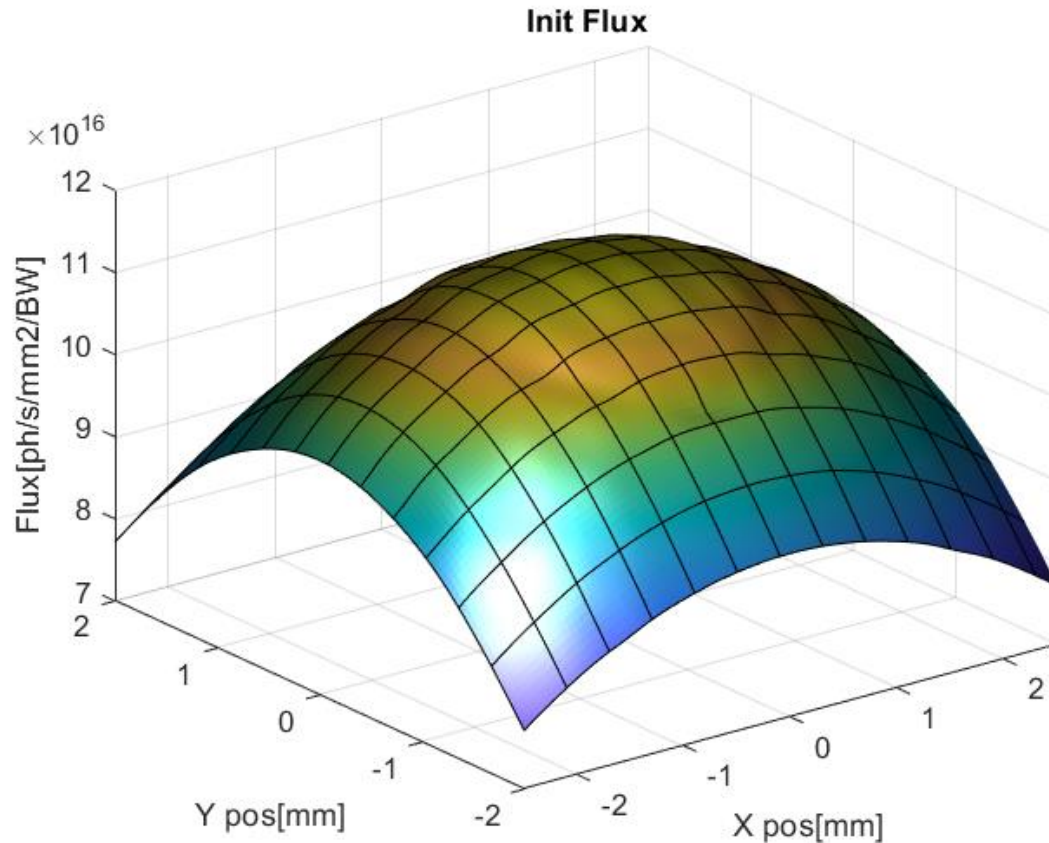


flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over energy, assuming 0.1%BW) FLUX



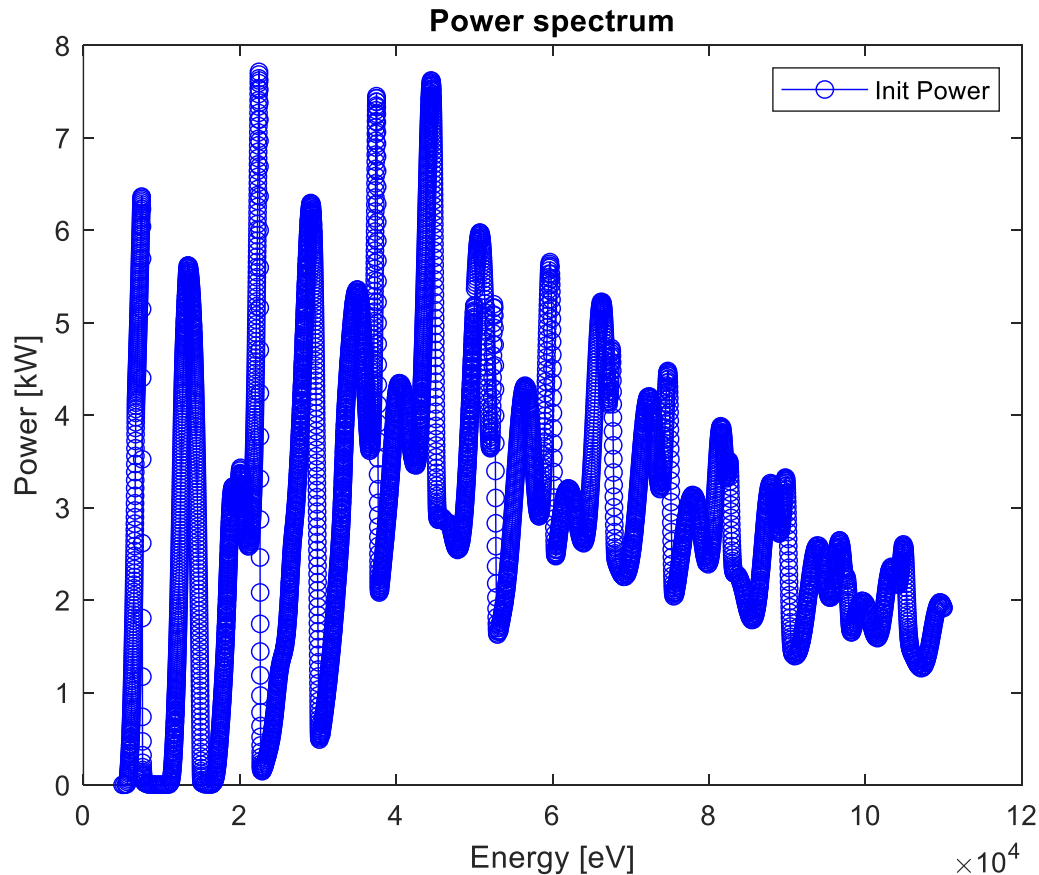
NOTICE:
simmetric profile

flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over *space*, assuming 0.1%BW) POWER

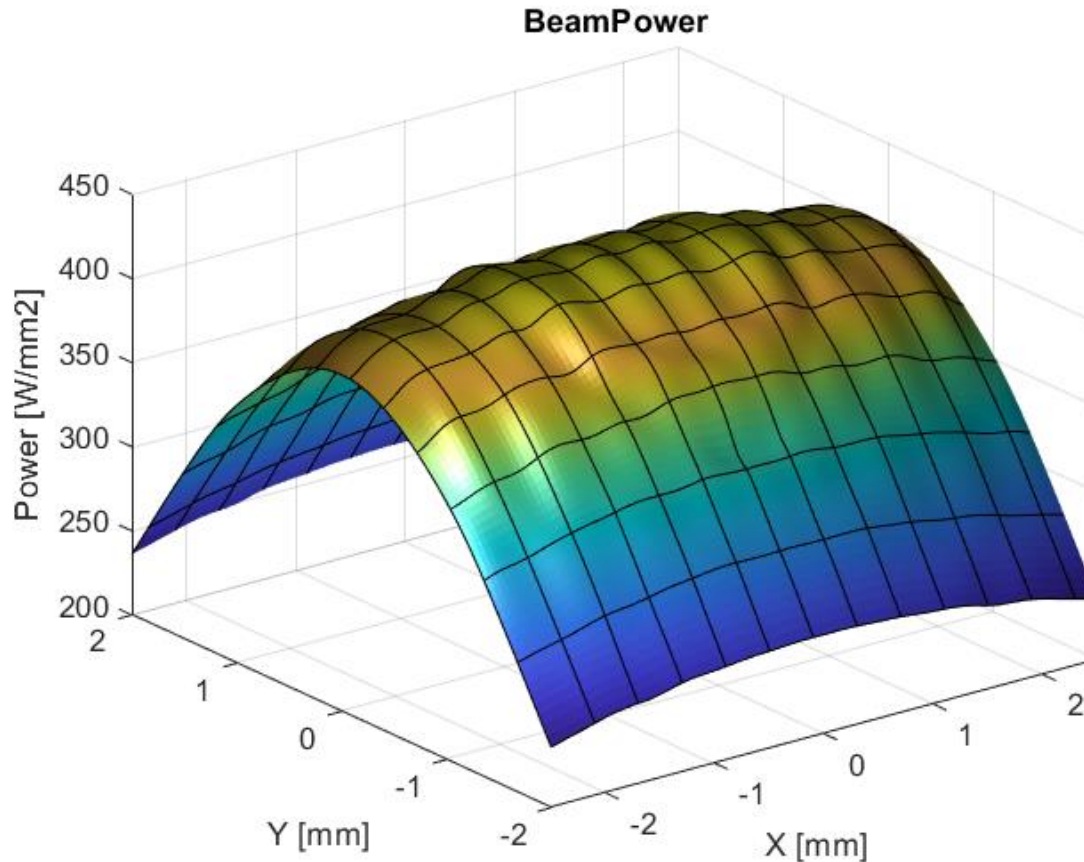


flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over energy, assuming 0.1%BW) POWER

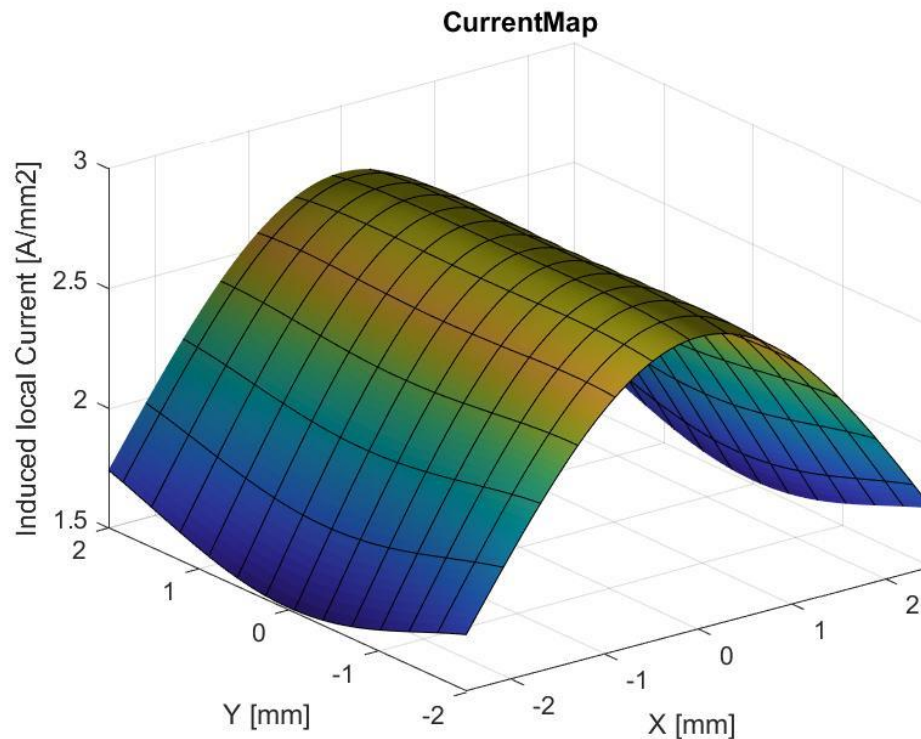


NOTICE:
elongation along X

flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)
3000 steps between 50keV-110keV (20eV steps)

Integrated (over energy, assuming 0.1%BW) ABSORBED POWER (2um SiC XBPM)



NOTICE:
elongation along Y!!

Lateral resolution
[1.12um, **36.3um**]

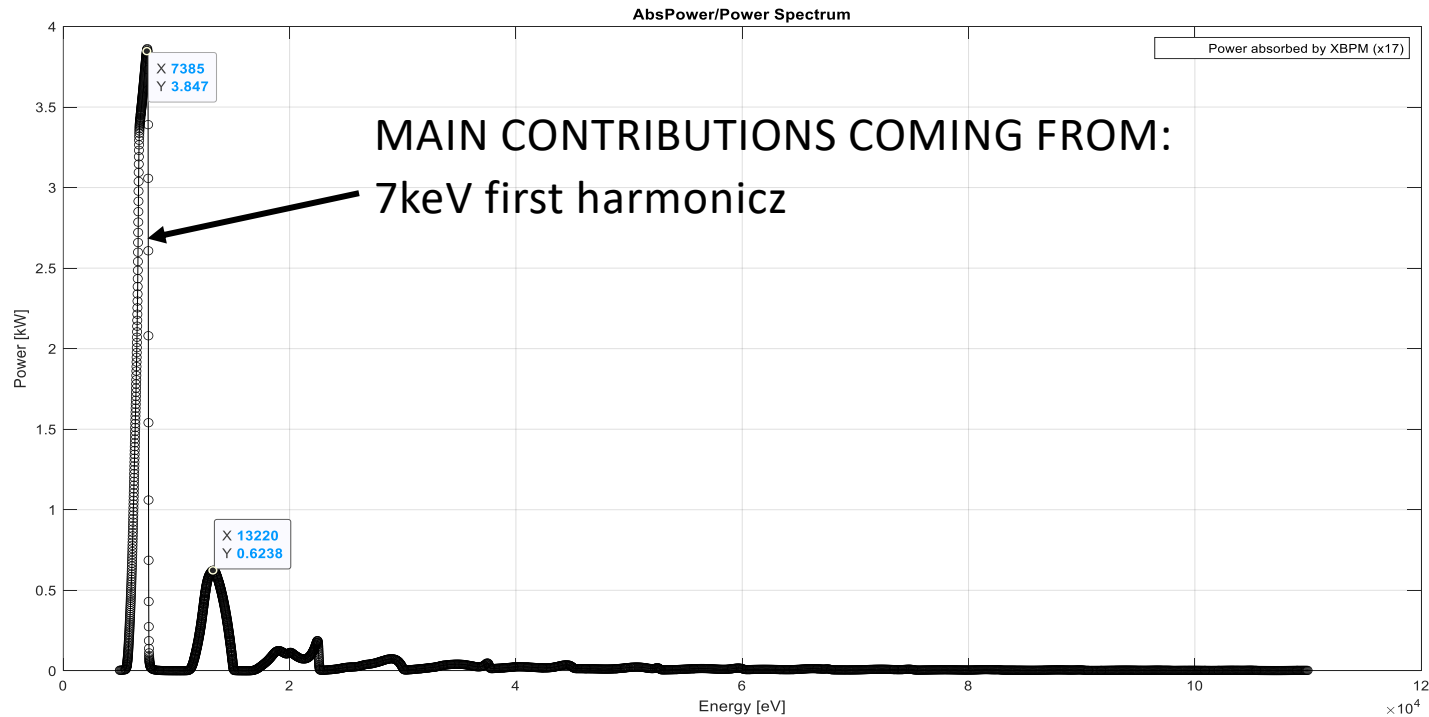
Max current on device
1.4[A]

flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over *space*, assuming 0.1%BW) ABSORBED POWER (2 μ m SiC XBPM)

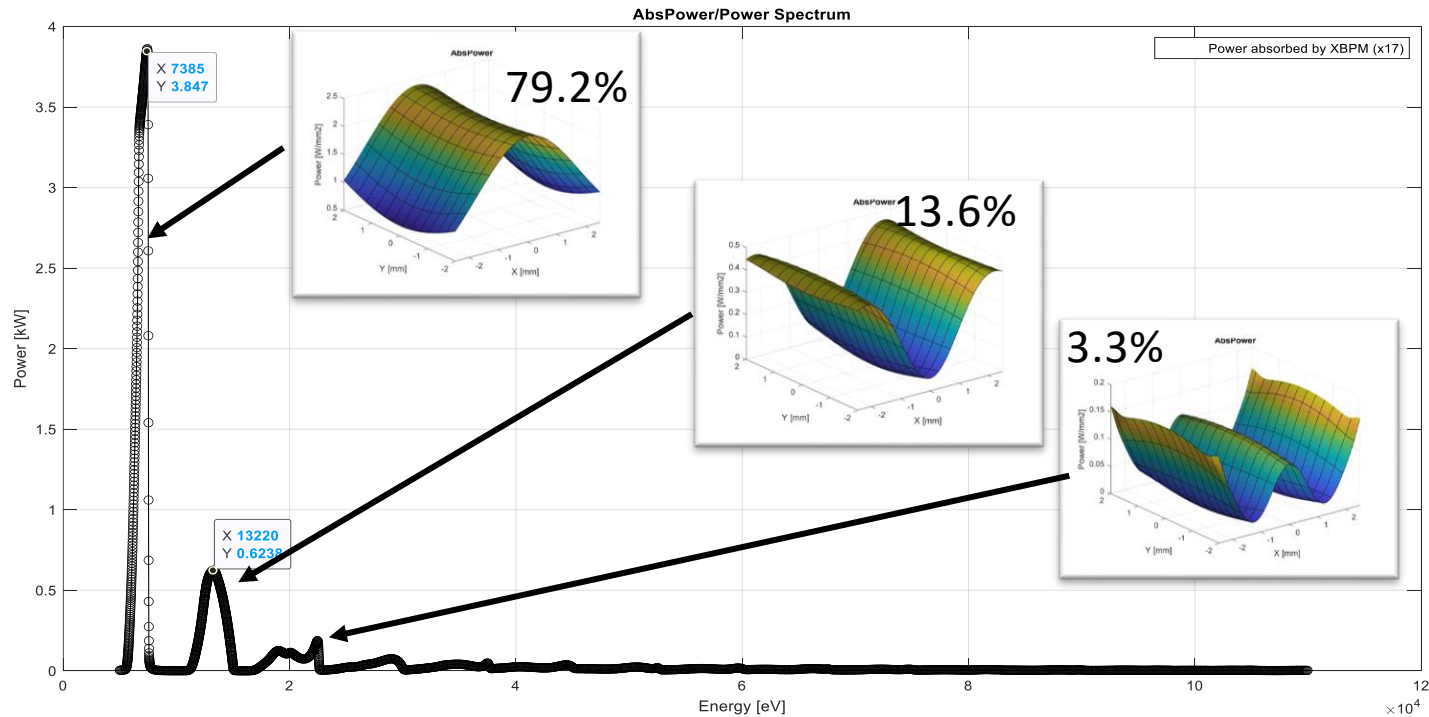


flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over *space*, assuming 0.1%BW) POWER ABSORBED BY DEVICE (STD, 2 μ m)

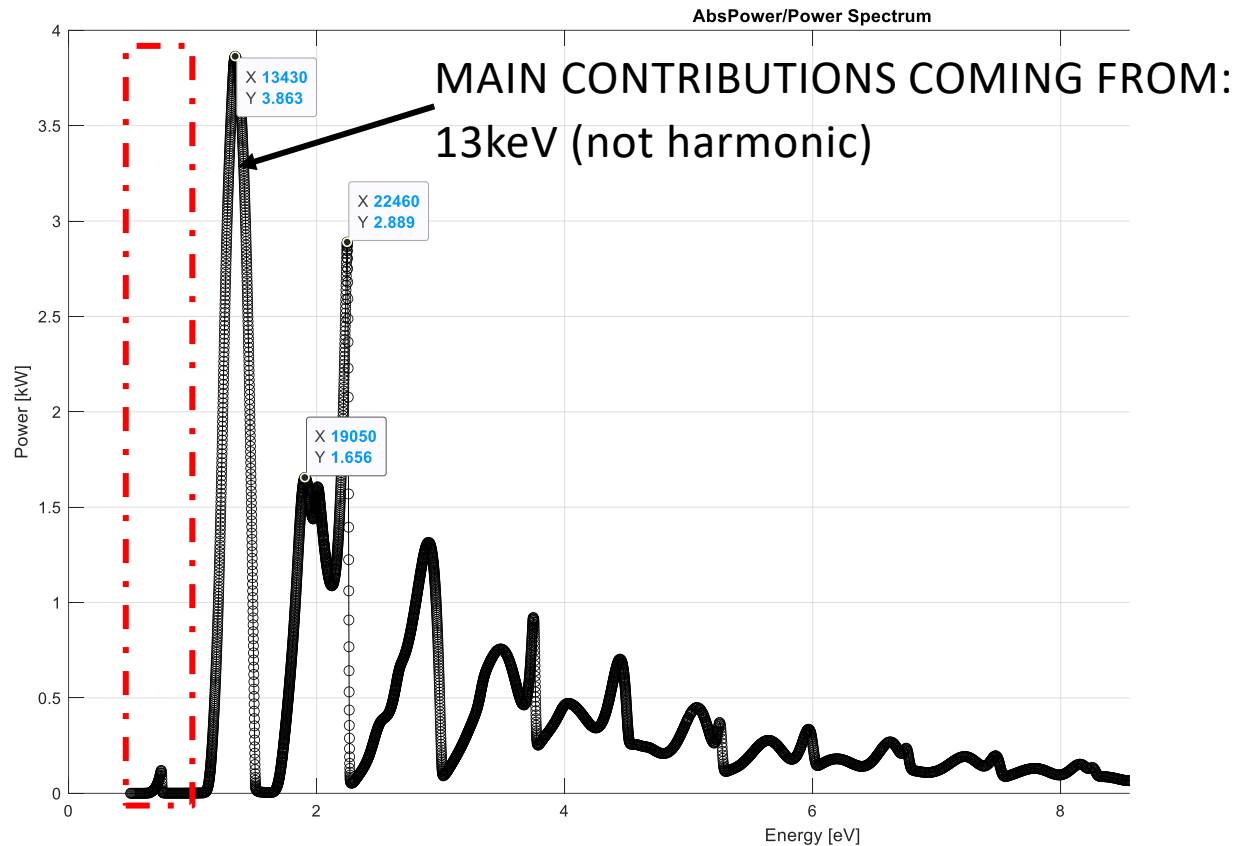


flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over *space*, assuming 0.1%BW) POWER ABSORBED BY DEVICE (*FILTERED BLADE*, 2 μ m)

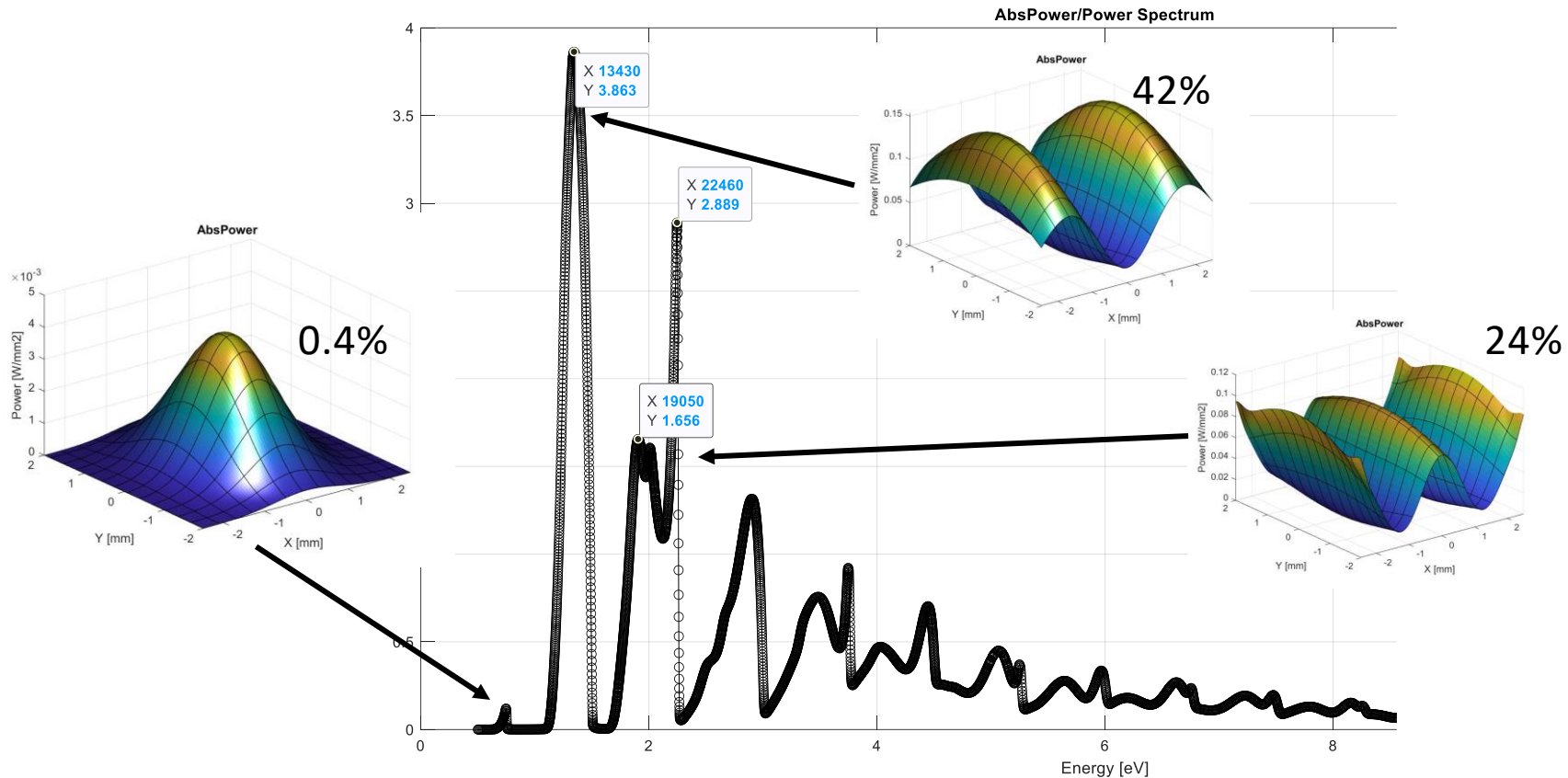


flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

3000 steps between 50keV-110keV (20eV steps)

Integrated (over *space*, assuming 0.1% BW) POWER ABSORBED BY DEVICE (FILTERED BLADE, 2 μ m)



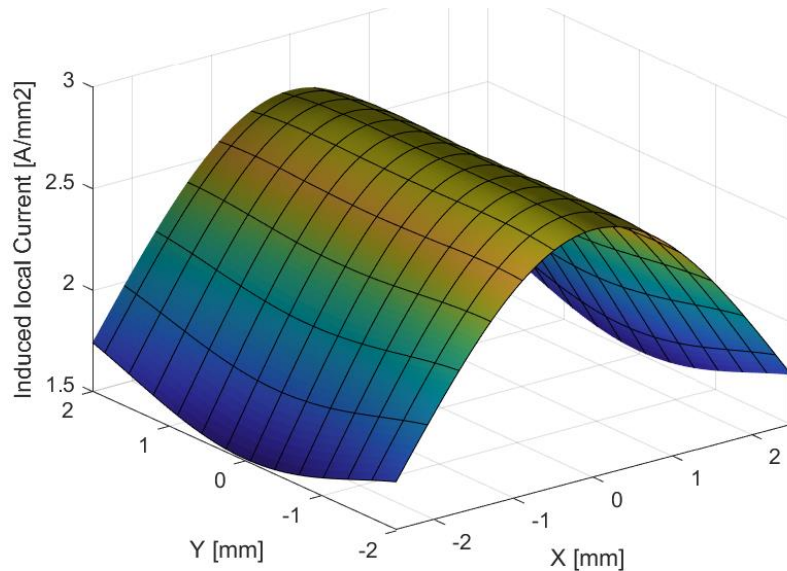
flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)

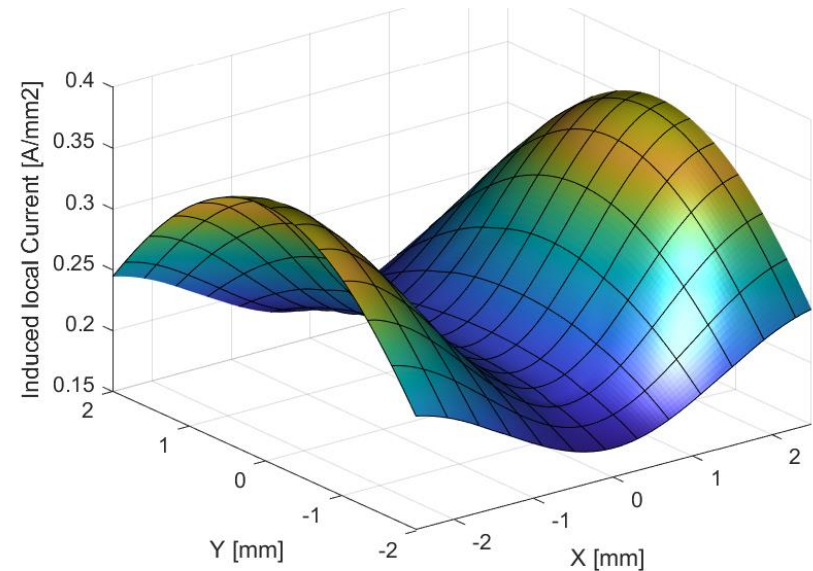
3000 steps between 50keV-110keV (20eV steps)

DEVICE CURRENT MAPs comparison

STD “blade”



FILTERED “blade”

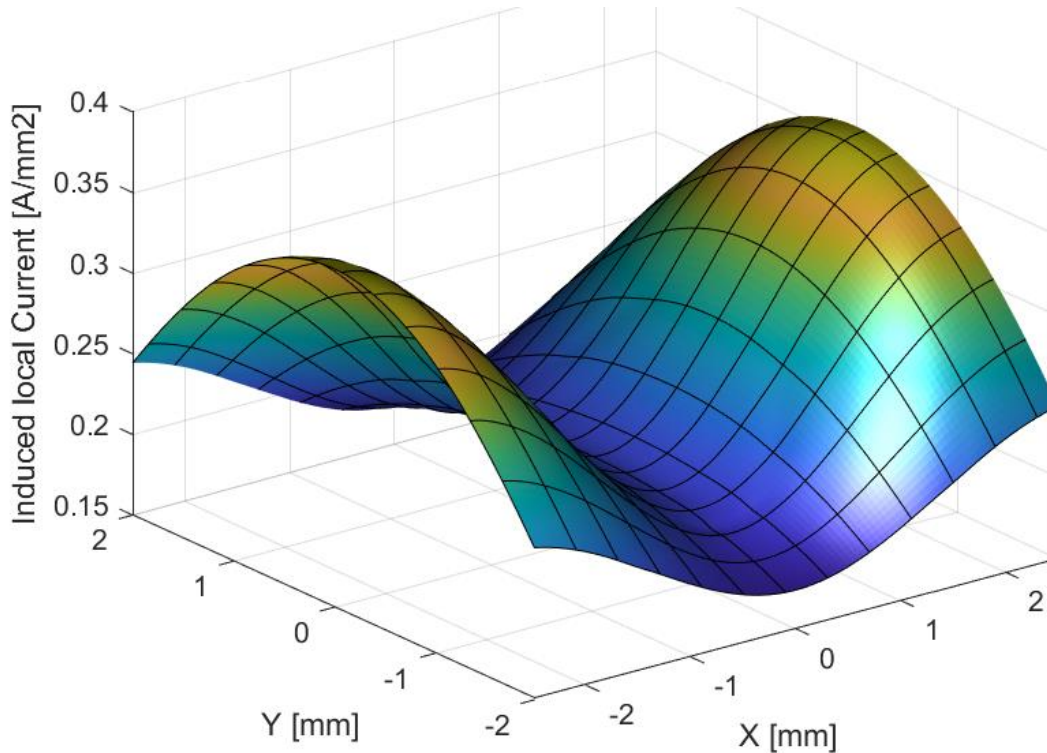


Very different profiles

related to different shape of 1th and 2th harmonics

massimo.camarda@SenSiC.ch

Integrated (over energy, assuming 0.1%BW) ABSORBED POWER (2um SiC OPT XBPM)



Lateral resolution
 [0.46um, **2.7um**] ^{x10}
Max current on device
90[mA]

flux maps energy calculations:

6000 steps between 500-50000eV (7eV steps)
 3000 steps between 50keV-110keV (20eV steps)

Goal of SenSiC is to develop X-ray diagnostic at all levels, using a novel material and *customized* technologies

What is now (installed):

1. Standard SiC XBPM with better characteristics than diamond
2. SiC sensors alternative to gas chambers (I0)
3. SiC sensors for absorption measurements (beam-stopper)
4. “Ultra-compact” SiC sensors alternative to xray eyes (nano-focusing)
5. Feedback system for (slow) shift during spectral measurements

What we are currently working on:

1. Fast and complete readout and feedback control loops
2. Monitors for small angles scattering measurements (XBPM beam-stopper)
3. Monitors for profile monitors (X-ray imaging)
4. Resistive Xray position monitors (single pixes sensors)
5. Whitebeam and crosschromatic monitoring

SiCblades™ detectors can:

withstand (easily) extreme high powers

be used for both soft- and hard-Xray beamlines

be optimized to yield very high lateral resolutions

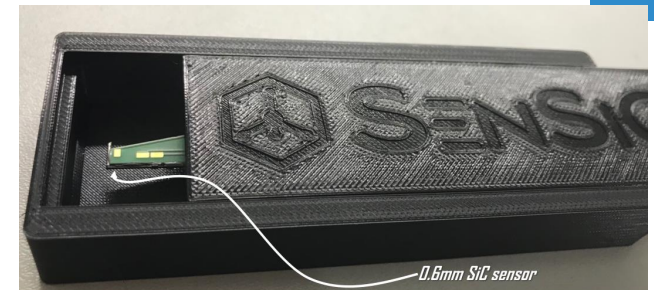
be optimized to avoid bending magnet background radiation

have multiple “pixels” to reconstruct asymmetric distributions



THANKS FOR YOUR ATTENTION!

SENSIC^{CH}



massimo.camarda@SenSiC.ch